

Europäisches Patentamt  
European Patent Office  
Office européen des brevets



(11) EP 0 816 926 A2

(12)

## EUROPEAN PATENT APPLICATION

(43) Date of publication:  
07.01.1998 Bulletin 1998/02

(51) Int Cl.<sup>6</sup>: G03F 7/20

(21) Application number: 97304889.5

(22) Date of filing: 04.07.1997

(84) Designated Contracting States:  
AT BE CH DE DK ES FI FR GB GR IE IT LI LU MC  
NL PT SE

• Yoshii, Minoru  
Ohta-ku, Tokyo (JP)

(30) Priority: 05.07.1996 JP 176432/96  
04.10.1996 JP 264383/96

(74) Representative:  
Beresford, Keith Denis Lewis et al  
BERESFORD & Co.  
2-5 Warwick Court  
High Holborn  
London WC1R 5DJ (GB)

(71) Applicant: CANON KABUSHIKI KAISHA  
Tokyo (JP)

(72) Inventors:  
• Takeuchi, Seiji  
Ohta-ku, Tokyo (JP)

### (54) Exposure apparatus

(57) A pattern inspection system for detecting a state of a pattern formed on an object (13), includes a light projecting device (31a) for projecting input light on to a sensitized pattern defined on the object, a light receiving device (32a) for receiving signal light from the sensitized pattern, a processing device (34) for detect-

ing a change in the light by use of a signal from the light receiving device to detect the state of formation of the sensitized pattern, and a control device (33,54) for changing a condition of incidence (angle, wavelength, polarisation, intensity) of light from the light projecting device.

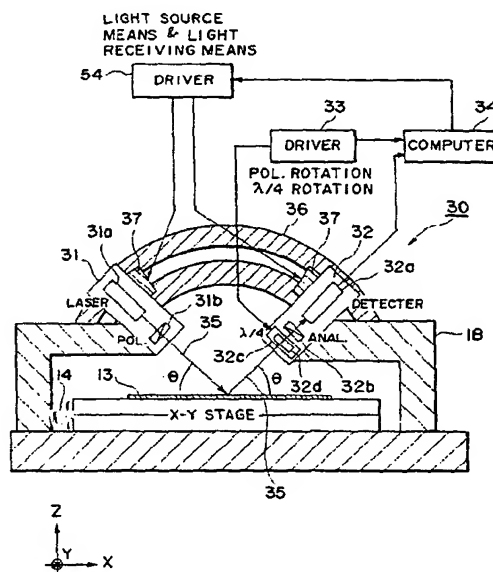


FIG. 2

EP 0 816 926 A2

## Description

This invention relates to an exposure apparatus and, more particularly, to a pattern inspecting system or a substrate processing procedure monitoring system using such an inspection system. In another aspect, the invention is concerned with an exposure apparatus having an inspection system or a substrate processing procedure monitoring system such as above. The present invention is particularly suitable for determination of optimum exposure condition promptly or in real time to perform an exposure step in lithographic process, among manufacturing processes for production of devices such as semiconductor devices (e.g., IC or LSI), image pickup devices such as CCD, display devices such as liquid crystal panels, or magnetic heads, for example, on the basis of monitoring procedure in a processing system used in the lithographic process. The invention is applicable specifically for detection of any failure in a processing step promptly, to ensure process control.

Recently, the degree of integration of semiconductor device such as IC or LSI has been increased considerably, and fine processing technology of semiconductor wafer has also been much advanced. In this fine processing technology, many proposals have been made to a reduction projection exposure apparatus (stepper) wherein an image of a circuit pattern of a mask (reticle) is formed on a photosensitive substrate by a projection optical system (projection lens) and wherein the photosensitive substrate is exposed in step-and-repeat method.

In such steppers, a circuit pattern of a reticle is projected, in a reduced scale, at a predetermined position on the surface of a wafer through a projection optical system having a predetermined reduction magnification. After completion of one projection transfer operation, a stage on which the wafer is placed is moved by a predetermined amount. Then, the transfer operation is repeated. This procedure is repeated to perform exposure of the whole wafer surface.

Generally, in order to assure transfer of fine circuit pattern by use of a stepper having a projection optical system, it is important to set exposure condition such as wafer exposure amount or wafer focus position (wafer position with respect to a direction of an optical axis of the projection optical system) appropriately.

To this end, in conventional steppers, trial printing process (send-ahead) is performed prior to initiation of mass-production procedure. In such trial printing process, the exposure condition, that is, at least one of focus position and exposure amount (shutter time) is changed successively with respect to different shots. After printing of a photosensitive substrate, it is treated by a developing process, and the line width of a straight pattern developed is measured by use of an optical microscope or a line-width measuring device. Optimum exposure condition is then determined.

As regards lateral direction of wafer shot layout, for example, the exposure process may be performed with constant focus value while changing exposure amount (shutter time) successively by regular amount. As regards longitudinal direction of the wafer shot layout, the exposure process may be performed with constant exposure amount while changing focus value successively by regular amount.

Then, the line width of a resist pattern (L&S pattern) of lines and spaces in each shot, as defined through the developing process, may be measured by use of a scanning electron microscope (SEM). On the basis of this, optimum focal point position and optimum exposure amount may be determined.

In this procedure, however, measurement of the line width of a resist pattern on a wafer through a scanning electron microscope, for example, for setting optimum exposure condition (exposure amount or focus position) in steppers requires a long processing time.

Further, an exposure wafer has to be processed by a developing step, an etching step and an ashing step, for example. Through these steps, a final pattern is formed on the wafer. Thus, depending on a condition in such processing step after exposure, there is a possibility that the state of formation of such final pattern on the wafer varies.

In mass-production of devices, the state of formation of such pattern should desirably be constant. However, due to various factors, the condition in a processing step may change which in turn may cause a decrease in yield. It is therefore necessary to monitor the processing step periodically and to control the same.

Usually, such process control is based on measurement of a line width of a straight pattern by use of an optical microscope or a line-width measuring device. Thus, it takes a long time for the process control.

It is an object of the present invention to provide a pattern inspection system by which optimum exposure condition can be determined in a short time period.

It is another object of the present invention to provide a projection exposure apparatus having such a pattern inspection system.

In a pattern inspection system of the present invention, the state of sensitization of a resist sensitized by exposure (i.e. latent image) or the state of formation of a sensitized pattern such as a line-and-space pattern after being developed, is measured on the basis of a change in light projected under different light incidence conditions, for example, a change in intensity of reflection light or a change in state of polarization. An optimum exposure condition is determined on the basis of a measured value. Mass-production exposure of wafers is performed under that optimum exposure condition.

It is a further object of the present invention to provide a substrate processing step monitoring system by which quick and assured process control is enabled and production of large-integration pattern is enabled. In a substrate

processing step monitoring system of the present invention, for control of a developing step, for example, the state of sensitization of an exposed resist (i.e. latent image) before developing process and the state of formation of a sensitized pattern such as a line-and-space pattern after the developing process, are measured on the basis of a change in projected light, for example, a change in intensity of reflection light or a change in state of polarization. Then, on the basis of comparison of measured values, a change in state of pattern formation is detected and whether the fault has been created during the developing process or before the developing process is discriminated.

In accordance with a further aspect of the present invention, there is provided a pattern inspection system for detecting a state of a pattern formed on an object, said system comprising: light projecting means for projecting input light on to a sensitized pattern defined on the object; light receiving means for receiving signal light from the sensitized pattern; processing means for detecting a change in the light by use of a signal from said light receiving means to detect the state of formation of the sensitized pattern; and control means for changing a light incidence condition of light from said light projecting means.

In accordance with a still further aspect of the present invention, there is provided a projection exposure apparatus for projecting a pattern of a first object, as illuminated with exposure light, on to a second object coated with a photosensitive material through a projection optical system to thereby form a sensitized pattern on the second object, said apparatus comprising: light projecting means for projecting input light on to the sensitized pattern with different conditions of light incidence; light receiving means for receiving signal light from the sensitized pattern; and processing means for detecting a change in the input light by use of a signal from said light receiving means to detect the state of formation of the sensitized pattern.

In accordance with a yet further aspect of the present invention, there is provided a projection exposure method for projecting for projecting a pattern of a first object on to a second object coated with a photosensitive material through a projection optical system, said method comprising the steps of: illuminating the pattern of the first object with exposure light while changing an exposure condition and projecting the pattern of the first object so illuminated on to the second object, whereby a plurality of sensitized patterns are formed on the second object; projecting input light from light projecting means to the sensitized patterns under different conditions of light incidence; receiving, through light receiving means, signal light from the sensitized patterns; detecting a change in input light by use of a signal from the light receiving means to detect a state of formation of the sensitized patterns through processing means; and controlling exposure condition of the second object through control means, on the basis of a signal from the processing means.

In accordance with a further aspect of the present invention, there is provided a substrate processing procedure monitoring system, comprising: light projecting means for projecting input light on to a pattern defined on a substrate; light receiving means for receiving signal light from the pattern; detecting means for detecting a change in input light by use of a signal from said light receiving means; and processing means having inspecting means for detecting a state of formation of the pattern on the basis of detection by said detecting means, for memorizing and comparing results of detection of the state of formation of the pattern before and after the processing procedure to the substrate.

In accordance with a still further aspect of the present invention, there is provided a substrate processing procedure monitoring method, comprising the steps of: projecting input light on to a periodic pattern defined on a substrate; receiving, through light receiving means, signal light from the pattern; detecting a change in input light by use of a signal from the light receiving means; detecting a state of formation of the pattern on the basis of detection at said detecting step; and memorizing and comparing results of detection of the state of formation of the pattern before and after the processing procedure to the substrate.

Embodiments of the present invention will now be described with reference to the accompanying drawings, in which:-

Figure 1 is a sectional view of a main portion of an arrangement according to an embodiment of the present invention.

Figure 2 is a sectional view of a polarization analysis system of the arrangement of Figure 1.

Figure 3 is a schematic view for explaining focus detection and exposure amount control in an exposure apparatus.

Figure 4 is an enlarged top plan view of a reticle pattern for measurement of exposure condition.

Figure 5 is a schematic view for explaining a resist latent image on a wafer, being printed with varying exposure condition.

Figures 6A - 6C are schematic and sectional views, respectively, each for explaining a resist latent image on a wafer of Figure 5.

Figure 7 is a schematic view for explaining calibration of a measured value of a polarization analysis system, through a scanning electron microscope (SEM).

Figure 8 is a graph of  $\Delta\phi$  map.

Figure 9 is a flow chart of a procedure in a case where polarization analysis method is applied for exposure condition setting.

Figure 10 is a schematic view for explaining polarization analysis method.

Figure 11 is a schematic view of an arrangement according to another embodiment of the present invention, wherein

a polarization analysis system is disposed separately.

Figure 12 is a schematic view of an arrangement according to a further embodiment of the present invention, wherein a polarization analysis system is disposed separately.

Figure 13 is a schematic view for explaining examples of sectional shape of a resist after a development process.

5 Figure 14 is a flow chart of a procedure wherein a development process is added.

Figure 15 is a schematic view of an arrangement according to an embodiment of the present invention, wherein a development process is added.

Figure 16 is a flow chart of device manufacturing processes according to an embodiment of the present invention.

Figure 17 is a flow chart of a wafer process included in the procedure of Figure 16.

10 Figure 18 is a sectional view of a main portion of an arrangement according to an embodiment of the present invention.

Figure 19 is an enlarged top plan view of a measurement pattern.

Figure 20 is a schematic view for explaining resist latent images, in section.

Figure 21 is a schematic view for explaining a structure for polarization analysis.

15 Figure 22 is a top plan view for explaining an arrangement according to another embodiment of the present invention.

Figure 23 is a flow chart of a procedure to be done in the arrangement of Figure 22.

Figure 24 is a graph for explaining a tolerable range for pattern measurement with a polarization analysis system.

Figure 25 is a flow chart of a procedure to be done in another embodiment of the present invention.

20 Figure 26 is a flow chart of a procedure to be done in a further embodiment of the present invention.

Figure 27 is a flow chart of a procedure to be done in a still further embodiment of the present invention.

First, optimum exposure condition setting for projection exposure for printing a pattern of a first object (reticle) on a second object (wafer) by projection, will be explained.

25 When a pattern is transferred to a resist, an average value or effective value of refractivity of a resist pattern varies with a change in (a) focus position and (b) exposure amount.

More specifically, as a reticle (R), a mask with an exposure condition measurement pattern which comprises a line-and-space pattern having a periodicity in one direction, for example, is used, and images of such reference pattern are printed sequentially onto a wafer (W) while changing at least one of the exposure amount and the focus.

30 Latent image in the resist material on the wafer defined through this sequential exposure (i.e., an image defined by a portion whose refractivity has been changed due to chemical change caused by exposure) or a protrusion-recess pattern (rectangular-wave-like pattern) on the wafer formed after a development process is then irradiated with input light from a light projecting means under different light incidence conditions. Signal lights from the sensitized patterns are received by light receiving means. By using signals from the light receiving means, changes in input light (changes in state of polarization of input light or changes in intensity of it) are detected. On the basis of detection of changes in plural lights corresponding to the different light incidence conditions, respectively, the state of formation of the sensitized pattern is detected through processing means. Then, on the basis of a signal from the processing means, control means controls the exposure condition to the wafer (i.e., exposure amount or position with respect to an optical axis direction, for example).

35 Now, an example of such a change of light will be explained, with reference to a case where the state of polarization of input light changes.

40 For a sensitized pattern, light having a predetermined wavelength and a predetermined state of polarization is projected on to a resist with a predetermined angle of incidence. The light is transmitted through the resist. The light is reflected by the surface of the wafer bottom substrate, and it is transmitted again through the resist. The light going out of the resist is combined with the light having been directly reflected by the surface of the resist. The state of polarization of such combined light is measured.

45 It is known that, for a protrusion-recess pattern phase type diffraction grating, no diffraction light is produced with a wavelength longer than the pitch thereof, and it has a double refraction characteristic.

50 In an embodiment of the present invention, description will be made mainly on a case where reflection light is detected. However, if the pitch of a resist pattern is larger than the wavelength, diffraction light is produced. Similar measurement is attainable with such diffraction light.

55 Now, a polarization analysis method used in an embodiment of the present invention will now be explained. It is now assumed that grating thickness is  $d$  and duty ratio (the ratio of a remaining resist portion to the period) is  $t$ , and also that laser light having a wavelength greater than the period is perpendicularly incident on a double refraction element. Here, it is known that, depending on whether the state of polarization of the input or projected light is parallel to or perpendicular to the grating groove, refractivities  $n_{||}$  and  $n_{\perp}$  in the periodic structure portion of the double refraction element are given by the following equations. When effective refractivity with respect to light parallel to the grating groove is  $n_{||}$ , and effective refractivity with respect to light perpendicular to the grating groove is  $n_{\perp}$ , then:

$$n_{||} = \sqrt{(t \cdot n_1^2 + (1-t) \cdot n_2^2)}$$

$$n_{\perp} = 1/\sqrt{(t/n_2^2 + (1-t)/n_1^2)}$$

where  $n_1$  and  $n_2$  are refractivities of the line portion and of the space portion of the grating. The line portion L and the space portion S are such that, for a case of resist latent image, L corresponds to a resist and S corresponds to an exposed resist. When the resist is developed, L corresponds to a resist and S corresponds to a gas such as an air.

The equations of refractivity mentioned above are approximation equations in a case where the period of the periodic structure is sufficiently small as compared with the wavelength. If the electric field is calculated exactly, the refractivity can be calculated also in a case where the period is the same as or similar to the wavelength or a case where a structure other than a periodic structure is used.

A model of polarization analysis corresponds to measurement double refractivity of a double refractivity medium of a predetermined thickness, on a wafer substrate. The polarization analysis method is such that rectilinearly polarized light having a zero P/S phase difference (between P-polarization and S-polarization) and having an amplitude ratio of 1 is projected upon a wafer substrate, such as above, with a predetermined angle  $\theta$ , and phase difference ( $\Delta$ ) and amplitude ratio ( $\phi$ ) of reflected light therefrom are measured, to thereby determine  $n_{||}$  and  $n_{\perp}$ . Then, from the refractivities  $n_1$  and  $n_2$  of the line portion L and of the space portion S and resist thickness  $d$ , having been measured beforehand, and from the values of  $n_{||}$  and  $n_{\perp}$  determined in accordance with the polarization analysis method described above, duty  $t$  is determined by use of the equation mentioned above or the equation solved exactly. Since such polarization analysis method is known in the art, description of details of it will be omitted.

As regards the light incidence condition (e.g., incidence angle, azimuth angle with respect to pattern direction, wavelength), optimum condition varies with the refractivity of resist, film thickness thereof or the shape of the pattern. The condition also varies for a developed resist pattern measurement and for a latent image resist pattern measurement. Further, for a latent image, since the difference in refractivity between an exposed portion and an unexposed portion is small, in order that a minute change to be produced in pattern shape with a small change in exposure condition is resolved and detected with a small change in light, measurement may be made with such incidence condition that a large change is produced in light with exposure condition.

An embodiment of the present invention is thus arranged to provide a system whereby light can be projected under different incidence conditions, such that, on the basis of polarization analysis method as above, the duty of a latent image pattern of a resist or of a protrusion-recess pattern image after developed is measured.

In an embodiment of the present invention, from a value measured under a certain light incidence condition, an optimum light incidence condition is calculated, and, with the measurement of such optimum light incidence condition, measurement of enhanced resolution is enabled.

In accordance with polarization analysis method, there are cases wherein, depending on light incidence condition, the same polarization state is reproduced with different resist film thicknesses or different resist pattern shapes. In consideration of this, in an embodiment of the present invention, a change in reflection light under different light incidence conditions is detected such that different resist shapes, which may otherwise appear as being overlapped, may be resolved under a different light incidence condition, whereby a measured value is produced.

An embodiment of the present invention comprises a step for transferring a line-and-space pattern on to a photo-sensitive substrate with different exposure conditions to thereby form plural sensitized patterns thereon, a step for projecting light to the sensitized patterns sequentially and detecting states of polarization of lights from the patterns to thereby calculate duties of the sensitized patterns on the basis of the polarization states, a step for determining an exposure condition with which a desired duty is attainable, and a step for printing wafers under the determined exposure condition, wherein the light projecting means is arranged to provide different light incidence conditions for the light to be projected.

#### [First Embodiment]

A first embodiment of the present invention will now be explained with reference to drawings.

Figure 1 is a schematic view of a main portion of a first embodiment of the present invention, and Figures 2 - 5 are schematic views, respectively, corresponding to portions of Figure 1, respectively.

In this embodiment, a change in state of polarization is to be detected as a change in input light through a sensitized pattern.

In Figure 1, denoted at 11 is a reduction projection lens for projecting a circuit pattern 12a on the surface of a reticle 12, illuminated with exposure light from an exposure light source 17 (to be described later) on to the surface of a wafer 13. Denoted at 14 is a wafer chuck to which the wafer 13 is attracted. Denoted at 15 is a rough-motion and fine-motion

stage for providing rough-motion and fine-motion of the wafer chuck 14 in Z direction. Denoted at 16 is an X-Y stage for moving the wafer chuck 14 in X and Y directions. Denoted at 17 is an exposure light source, and denoted at 18 is a structure for supporting the light source 17, reticle 12, barrel 1, wafer stage 16, and arch 36.

Referring to Figure 4, description will be made of control means which includes a focus position control system for detecting the focus position, i.e., the position of the wafer 13 with respect to an optical axis direction of the projection lens 11, and an exposure amount control system to be used in relation to illumination of the reticle 12 with exposure light.

In Figure 3, denoted at 21 is a high-luminance light source such as a semiconductor laser, for example. Laser light from the light source 21 is deflected by a deflection mirror 28 and, after this, it is projected upon the surface of the wafer 13. After being reflected at a measurement point P1 on the wafer 13, the light is deflected by a deflection mirror 29 and is projected upon a detecting device 22 which serves to detect a two-dimensional position of light incident thereon. The detecting device 22 comprises a CCD, for example, and it functions to detect the position of incidence of light thereupon. Here, a change in position of the wafer 13 surface with respect to Z direction (optical axis direction of the projection lens 11) can be detected as a positional displacement of the incidence position of light upon the detecting device 22. On the basis of a signal from this detecting device 22, the focus control system 23 controls the Z-axis position of the wafer 13, i.e., the focus position, with use of the rough-motion and fine-motion stage 105.

Denoted at 26 is a shutter opening/closing mechanism, and denoted at 27 is a half mirror. Denoted at 25 is an illuminance sensor for detecting the amount of exposure with light from the light source 17, as reflected by the half mirror 27.

Integration exposure amount control device 24 serves to control the shutter opening/closing mechanism 26 on the basis of a signal from the illuminance sensor 25, to thereby control integrated exposure amount with the light from the light source 17. With this procedure, the exposure amount, irradiating the reticle 12, is controlled to a predetermined amount.

In this embodiment, control means having an exposure amount control system and a focus position control system such as described above is used to control the exposure condition for projection of a pattern of the reticle 12 on to the wafer 13 surface.

Next, description will be made on a case wherein a pattern of the reticle 12 illuminated with exposure light from the light source 17 is projected on to the wafer 13 surface.

Figure 4 illustrates a reference pattern 12P formed on the surface of a reticle 12. The reference pattern 12P comprises orthogonally arrayed line-and-space patterns 12V and 12H.

In this embodiment, the reticle 12 having a pattern 12P, comprising line-and-space patterns 12V and 12H, is set on the reticle stage 12a. A wafer 12 having a resist applied thereto is set on the wafer chuck 14. The pattern 12P of the reticle 12 is then sequentially printed on the wafer 13 in accordance with step-and-repeat method. Here, the focus control system 23 and the integration exposure amount control system 24 described above are used so that, as shown in Figure 6, zones (shots) 13P are printed sequentially whereby latent images 13V and 13H of the patterns 12V and 12H are printed.

Here, stepwise motion is performed while changing focus offset by regular amounts, about an expected optimum position (expected best focus position), in accordance with the shot position with respect to X direction. As regards the shots in Y direction, similarly, exposures are performed which changing the exposure amount, about an optimum exposure amount (shutter time). In the example of Figure 5, a matrix of 3x3 is illustrated for convenience of explanation. The more the number of shots is, the easier the determination of condition is.

Figures 6A - 6C are schematic views of a section of a resist of a wafer 13, having been exposed sequentially as described above. As shown in these drawings, in the resist of the wafer 13 after exposure, a latent image is formed. A latent image is an image having been defined by a change in property of the resist resulting from chemical change, for example, caused by exposure light. Hatched portions in the drawings represent portions having been exposed to light. Generally, the refractivity has been changed in these portions. The matrix addresses in Figures 6A - 6C corresponds to sections at those positions corresponding to the addresses in Figure 5. Figures 6A, 6B and 6C are sections taken on lines (1), (2) and (3) in Figure 5, respectively.

A resist of wafer 13 after exposure with latent images such as shown in Figures 6A - 6C is subjected to measurement of an amplitude ratio  $\phi$  and a phase difference  $\Delta$  of reflection light to light irradiated, by means of a polarization analysis system 30 which comprises a light source 31, a light receiving portion 32, a driver 33 and a polarization processing device 34, without being demounted from the wafer chuck 14.

Figure 2 is a schematic view of a main portion of such polarization analysis system 30 of Figure 1. Figure 10 is a schematic view, illustrating the same with optical paths being extended. In Figures 2 and 10, light source means (light projecting means) 31 comprises a light source 31a (which provides a wavelength longer than the line-and-space pitch on the wafer 13 and which may comprise a He-Ne laser or a semiconductor laser or, alternatively, monochromatic light from a spectrometer) and a polarization element 31b such as a Glan-Thompson prism, for example. The polarization element 31b has its polarization plane disposed at 45 deg. with respect to the sheet of the drawing, so that, with respect to the wafer 13, the same quantity of P-polarization component (parallel to the sheet of the drawing) and S-polarization

component (perpendicular to the sheet of the drawing) are provided. Thus, the phase difference  $\Delta$  between these P-polarized light and S-polarized light is zero, and an amplitude ratio  $\phi$  is 1.

The light receiving portion (light receiving means) 32 comprises a quarter wave plate 32d having its anisotropic axis perpendicular to the light 35, a polarization element (analyzer) 32b such as a Glan-Thompson prism, for example, and a photoelectric converting element 32a. The quarter wave plate 32d is held within a rotary mechanism 32c having a rotational axis along the light 35 direction. It is rotatable at a constant speed in response to a signal from a driver 33.

Light 35 from the light source means 31 is reflected by the surface of a resist on the wafer 13 and by the surface of the wafer substrate. In combined light of these reflection lights, the phase difference  $\Delta$  and amplitude ratio  $\phi$  of P-polarized component and S-polarized component vary in accordance with the double refractivity  $n_1$  and  $n_2$ , for example, of the resist on the wafer 13.

This light is detected by the detector 32a, by way of the rotating quarter wave plate 32d and analyzer 32b, whereby an electric signal of sine wave corresponding to the phase difference  $\Delta$  and amplitude ratio  $\phi$  is produced. Then, from positional information of sine wave of DC component magnitude and amplitude thereof, the phase difference  $\Delta$  and amplitude  $\phi$  are determined.

Then, from  $n_{||}$  and  $n_{\perp}$  as calculated from  $\Delta$  and  $\phi$  having been measured with polarization analysis method as well as from refractivity  $n_1$  of the unexposed portion of the resist, refractivity  $n_2$  of an exposed portion thereof, thickness  $d$  of the resist, and complex refractivity of the substrate, having been measured beforehand, the duty  $t_L$  (duty as  $n_{\perp}$  is used) is determined in accordance with the following equation:

$$t_L = n_1^2 \cdot (n_2^2 - n_{\perp}^2) / \{n_{\perp}^2 \cdot (n_2^2 - n_1^2)\}$$

Also, the duty  $t_{||}$  (duty as  $n_{||}$  is used) is given by:

$$t_{||} = (n_{||}^2 - n_2^2) / (n_1^2 - n_2^2)$$

By averaging these two values, the precision of duty  $t$  can be improved.

$$t = (t_L + t_{||}) / 2$$

In Figure 2, the light source means 32 and the light receiving portion 31 are fixed to the arch 36. As the driver 54 actuates the driving means 37 to move along the arch 36 in an arcuate path, the incidence angle can be changed. For example, when the subject of measurement is a latent image before a development process, since an optimum incidence angle with which the duty can be measured precisely varies with a resist used, an optimum angle can be selected in accordance with a difference in refractivity between an exposed portion and exposed portion, or the film thickness of the resist, for example. Further, since the optimum incidence angle varies largely between a case where the subject of measurement is a latent image before a development process and a case where it is a developed pattern after a development process, an incidence angle appropriate to the subject of measurement is set in response to a signal from a computer 34. More specifically, the light incidence condition (incidence angle) may be determined on the basis of changes in light under different incidence conditions.

On the other hand, Figure 7 illustrates how an optimum exposure condition is determined on the basis of comparison of a duty of a sample line-and-space, measured through polarization analysis, and a value having been provided by developing the same sample and by measuring it through a scanning electron microscope. An offset of a duty to be caused by an underlying bottom structure, when polarization analysis method is used, may be measured. In the following measurement, such an offset may be subtracted from a measured value, and a resultant value may be taken as a correct measured value. The comparison with use of a scanning electron microscope may be made only once when the condition such as a process is changed, and it is not necessary thereafter.

Next, the procedure of exposure condition optimization will be explained with reference to Figures 8 and 9. Figure 8 shows an example wherein chips of 8x6 are printed on one wafer and wherein results of polarization analysis to the same are illustrated in  $\Delta$ - $\phi$  map. For example, as regards measurement points on a line 70, the exposure amount is kept constant while the focus varies. On the other hand, as regards measurement points on a line 61, the focus is constant while the exposure amount varies.

The shots illustrated within a rectangular frame AX on this  $\Delta$ - $\phi$  map represents a range wherein an optimum duty is established, on the basis of scanning electron microscope measurement as described above. Thus, when an exposed shot is measured through polarization analysis method and if  $\Delta$  and  $\phi$  are within this frame AX, an optimum duty is indicated.

The procedure described above can be illustrated in a flow chart, such as shown in Figure 9. First, a resist is applied to a wafer. If the thickness of the resist is not known, it is measured at this stage. Subsequently, the stage is moved stepwise as described hereinbefore and trial printing is made while changing the focus and exposure amount (shutter time). In accordance with complex refractivity  $n_s$  of the substrate, refractivities  $n_1$  and  $n_2$  of an unexposed portion and exposed portion of the resist, thickness  $d$  of resist and wavelength  $\lambda$  used, the incidence angle  $\theta$  is set and fixed to such an optimum angle with which high measurement sensitivity is assured.

Subsequently, without unloading the wafer from the wafer chuck, the stage is moved similarly and, while changing shots successively,  $\Delta$  and  $\phi$  are measured in accordance with polarization analysis method. If the results of polarization analysis is within the predetermined range for  $\Delta$  and  $\phi$  shown in Figure 8, the exposure condition with which that shot has been printed is taken as an optimum exposure condition for mass-production printing.

The duty check based on polarization analysis method may be made at desired timings in the course of wafer mass-production printing procedure, whereby increased yield is assured. In this embodiment of the present invention, as described, an optimum exposure condition is set in the manner described above and, after that, a wafer is processed by a predetermined development procedure, whereby large-integration devices are produced.

While in the foregoing this embodiment has been described mainly with reference to a case wherein a latent image before development is taken as the subject of measurement, since in this embodiment the incidence angle is variable, it can be applied to polarization analysis of a developed pattern after development of a resist. Figure 13 illustrates sectional shapes of sensitized patterns, after resist development process, related to this embodiment. It is seen from Figure 13 that, since there is a large difference in refractivity between lines and spaces as compared with measurement to a latent image pattern (because the medium of refractivity  $n_2$  is a gas having a refractivity of about 1.0), this example is advantageous in the point of duty measurement precision. Thus, if the condition is restricted, measurement to a developed pattern may desirably be chosen.

Figure 14 is a flow chart in a case where a developed pattern is to be measured in accordance with this embodiment. In this case, a developer (developing apparatus) for resist development and a scanning electron microscope are used in combination, and measurement is made to a developed image, not a latent image. The scanning electron microscope may be used for calibration of pattern shape measurement based on polarization analysis, at the moment when checking of a developed resist image is required. Before start of measurement according to the flow chart of Figure 14, the incidence angle  $\theta$  is fixed in accordance with complex refractivity  $n_s$  of substrate, refractivity  $n_1$  and thickness  $d$  of resist, wavelength  $\lambda$ , for example, to an optimum angle with which high measurement precision is assured. After this is accomplished, the measurement procedure is performed.

#### [Second Embodiment]

A second embodiment of the present invention corresponds to an embodiment wherein, in the structure of Figure 2, the direction of light incidence is made variable. The term "direction of incidence" corresponds to an incidence azimuth angle which is defined, with respect to a certain direction upon a sensitized pattern surface, by a plane of incidence as defined by an axis of a projected light and a normal to the sensitized pattern. In Figure 2, there is a rotational stage (not shown) disposed below the X-Y stage underneath the wafer chuck 14. After the X-Y stage moves a sensitized pattern, just to be measured, to the position of light projection spot, the rotational stage rotationally moves the sensitized pattern relative to the light source means and the light receiving portion, toward an optimum direction of incidence appropriated to the substrate under a resist, the refractivities  $n_1$  and  $n_2$  of unexposed and exposed portions of the resist, the thickness  $d$  of resist, and the period, angle and number of lines of an exposed pattern. In this manner, polarization analysis measurement is performed with the direction of incidence with which high sensitivity measurement is assured. More specifically, light incidence condition (incidence azimuth angle) is determined on the basis of changes in light under different incidence conditions (incidence azimuth angles). The remaining portion of this embodiment is essentially the same as the first embodiment.

It is to be noted that a similar advantageous result is attainable when, in place of a rotational stage below the wafer X-Y stage, a driving system which is rotatable around an axis coincident with a normal to a wafer and passing through the point of incidence upon the arch 36 of Figure 2.

#### [Third Embodiment]

A third embodiment of the present invention corresponds to an embodiment wherein, in the structure of Figure 2, the wavelength of projected light is made variable. For example, the light source of the light source means 31 may comprise a combination of a halogen lamp and a spectroscope. When a latent image resist pattern is the subject of measurement, if measurement is made with use of a short wavelength close to a resist sensitizing wavelength, an unexposed portion is sensitized and it causes a change in pattern. In consideration of this, in this embodiment the measurement is made with use of a sufficiently long wavelength with respect to which a resist used does not have a

sensitivity. When on the other hand a developed resist pattern is the subject of measurement, since it is a pattern having been subjected to a development process, a high-sensitivity shorter wavelength is used to assure high-precision measurement.

Further, since optimum wavelength of projected light varies in accordance with the substrate under a resist, the refractivities  $n_1$  and  $n_2$  of unexposed and exposed portions of the resist, the thickness  $d$  of it, the period, angle and number of lines of an exposed pattern, for example, measurement may preferably be made with an optimum light wavelength suited to the subject of measurement. More specifically, the incidence condition (wavelength of projected light) is determined on the basis of changes in light under different incidence conditions (wavelengths of projected light).

The remaining portion of this embodiment is essentially the same as the first embodiment.

Similar advantageous result of variable wavelength of projected light is attainable with an arrangement wherein light from a halogen lamp is passed through a spectroscopy and, by using an optical fiber, the light from an exit port of the spectroscopy is directed to the light source means. Without use of a combination of a halogen lamp and a spectroscopy, a tunable laser or plural semiconductor lasers may be used with similar advantageous result.

#### [Fourth Embodiment]

Figure 11 is a schematic view of a fourth embodiment of the present invention. This embodiment differs from the first embodiment only in point that, in consideration of an occasion where there is some physical limitation within an exposure apparatus, a polarization analysis system is provided separately from a wafer stage of the exposure apparatus. The remaining portion has the same structure as of the first embodiment. Figure 12 illustrates a modified example of this embodiment. As compared with the fourth embodiment wherein polarization analysis is made to a latent image without development of a resist of a wafer, in the illustrated example a resist is developed and, thereafter, polarization analysis is performed.

#### [Fifth embodiment]

A fifth embodiment of the present invention is an example wherein measurement is made with use of different incidence angles for a single sensitized pattern. As compared with the first embodiment wherein one optimum incidence angle is determined on the basis of preparatively measured refractivities  $n_1$  and  $n_2$  of unexposed and exposed portions, resist thickness  $d$  and complex refractivity  $n_s$  of the substrate, in the present embodiment light is projected with different incidence angles and changes in light are detected. Thus, by using detected values with different incidence angles, high-precision measurement is assured.

In accordance with this embodiment of the present invention, the refractivities  $n_1$  and  $n_2$  of an unexposed portion and exposed portion, the resist thickness  $d$  and the complex refractivity  $n_s$  of the substrate, having been measured beforehand, are used to choose plural incidence angles close to an optimum incidence angle, and measurement is made with such incidence angles. When a certain shape of a sensitized pattern is assumed, a change in light as the light is incident at a desired incidence angle can be calculated. With respect to each of incidence angles with which measurement has been done, a change in light which is based on calculation with a certain duty  $t$  assumed and a change in light obtained through actual measurement are compared with each other. If, for example, the measurement is done with three incidence angles  $\theta_1$ ,  $\theta_2$  and  $\theta_3$ , the duty  $t$  may be so determined that a function which uses ratios  $\phi_1$ ,  $\phi_2$  and  $\phi_3$  of P-polarized light and S-polarized light obtained through measurement, phase differences  $\Delta_1$ ,  $\Delta_2$  and  $\Delta_3$  of P-polarized light and S-polarized light, ratios  $\phi_1'(t)$ ,  $\phi_2'(t)$  and  $\phi_3'(t)$  of P-polarized light and S-polarized light obtained with calculation, and phase differences  $\Delta_1'(t)$ ,  $\Delta_2'(t)$  and  $\Delta_3'(t)$  of P-polarized light and S-polarized light, i.e., the following function becomes minimum:

$$D(t) = \{\phi_1 - \phi_1'(t)\} + \{\phi_2 - \phi_2'(t)\} + \{\phi_3 - \phi_3'(t)\} \\ + \{\Delta_1 - \Delta_1'(t)\} + \{\Delta_2 - \Delta_2'(t)\} + \{\Delta_3 - \Delta_3'(t)\}$$

In this manner, the duty  $t$  can be measured precisely.

Further, since the film thickness of a resist varies as a result of exposure or development as is known in the art, optimization of incidence angle with respect to a thickness  $d$  measured beforehand does not necessarily result in determination of an optimum incidence angle. Since the state of polarization is variable even with the film thickness, for determination of the duty, the thickness  $d$  may be added as a parameter for calculation, and the duty  $t$  and thickness  $d$  may be so determined that the following function becomes minimum:

$$D(t) = \{\phi 1 - \phi 1'(t, d)\} + \{\phi 2 - \phi 2'(t, d)\} + \{\phi 3 - \phi 3'(t, d)\} \\ + \{\Delta 1 - \Delta 1'(t, d)\} + \{\Delta 2 - \Delta 2'(t, d)\} + \{\Delta 3 - \Delta 3'(t, d)\}$$

In this manner, the shape of a sensitized pattern can be measured more exactly. When the shape of a resist is to be determined practically, in consideration of many parameters it is desirable to perform the measurement through detected values obtained with use of different incidence angles. The remaining portion of this embodiment has substantially the same structure as of the first embodiment.

#### [Sixth Embodiment]

A sixth embodiment of the present invention is an example wherein measurement is made with use of different incidence directions for a single sensitized pattern. The direction of incidence refers to an incidence azimuth angle of a plane of incidence as defined by an optical axis of projected light and a normal to a sensitized pattern, with respect to a certain direction on the surface of the sensitized pattern. Similarly to the second embodiment, this embodiment includes in Figure 2 a rotational stage (not shown) disposed below the X-Y stage underneath the wafer chuck 14. After a sensitized pattern which is the subject of measurement is moved to the position of a projected light spot, polarization analysis is performed.

Light is projected to a pattern, in X direction. After this, the rotational stage is moved to rotationally move the sensitized pattern along X-Y plane by 90 deg. around the point of incidence of light, and measurement is made again with use of an incidence direction perpendicular to that in the preceding measurement operation.

The present embodiment meets a variation of measured value due to any resist unevenness or to the structure of an underlying substrate. More specifically, to polarization analysis measurement in a certain direction, second measurement is made to substantially the same measurement point in the preceding measurement in an incidence direction perpendicular to the direction in the preceding measurement. By doing so, precision can be increased as follows.

In this case, similarly to determination of  $t$  in the first embodiment,

$$t(90 \text{ deg.}) = (t_{\perp} + t_{\parallel})/2$$

By using  $t(0 \text{ deg.})$  calculated in the first embodiment, an average is determined:

$$t = \{t(0 \text{ deg.}) + t(90 \text{ deg.})\}/2$$

In this manner, measurement precision of duty  $t$  can be increased.

Also, for measurement to details of a shape of a pattern, not only measurement analysis in two directions of the plane of incidence parallel to grooves of a sensitized pattern and of the plane of incidence perpendicular to it, but also measurement analysis in an incidence direction intermediate between the two directions, may be required.

Similar advantageous result may be accomplished by using, in place of a rotational stage below a wafer X-Y stage, a driving system rotatable about an axis of normal to the wafer, passing the point of incidence upon the arch 36 in Figure 2. The remaining portion of the present embodiment has substantially the same structure as of the first embodiment.

#### [Seventh Embodiment]

A seventh embodiment of the present invention is an example wherein measurement is made with use of different wavelength for a single sensitized pattern. This embodiment is similar to the third embodiment and, in the structure of Figure 2, the light source for the light source means 31 is provided by a combination of a halogen lamp and a spectroscopy, for example.

In the third embodiment, measurement is done with one optimum incidence wavelength corresponding to a value or values of the subject of measurement, such as the underlying substrate, the refractivities  $n_1$  and  $n_2$  of unexposed and exposed portions of resist, the resist thickness  $d$ , the period, angle, number of lines of the exposed pattern, for example. In the present embodiment, as compared therewith, plural wavelengths are applied and changes in light are detected. By using a detected value obtained with use of plural wavelengths, high precision measurement is enabled.

In accordance with the present embodiment, plural wavelengths near an optimum wavelength are selected on the basis of preparatively measured values related to the subject of measurement, such as underlying substrate of resist,

refractivities  $n_1$  and  $n_2$  of unexposed and exposed portions of the resist, thickness  $d$ , and period, angle and number of lines of the exposure pattern, for example. The measurement is made by use of these wavelengths.

When a certain shape of a sensitized pattern is assumed as in the fifth embodiment, changes in light as a desired wavelength of light is applied can be calculated. With respect to each of the wavelengths applied, a change in light which is based on calculation with a certain duty  $t$  assumed and a change in light obtained through actual measurement are compared with each other. If, for example, changes in the state of polarization is measured with use of three wavelengths  $\lambda_1$ ,  $\lambda_2$  and  $\lambda_3$ , the duty  $t$  may be so determined that a function which uses ratios  $\phi_1$ ,  $\phi_2$  and  $\phi_3$  of P-polarized light and S-polarized light obtained through measurement, phase differences  $\Delta_1$ ,  $\Delta_2$  and  $\Delta_3$  of P-polarized light and S-polarized light, ratios  $\phi_1'(t)$ ,  $\phi_2'(t)$  and  $\phi_3'(t)$  of P-polarized light and S-polarized light obtained with calculation, and phase differences  $\Delta_1'(t)$ ,  $\Delta_2'(t)$  and  $\Delta_3'(t)$  of P-polarized light and S-polarized light, i.e., the following function becomes minimum:

$$D(t) = \{\phi_1 - \phi_1'(t)\} + \{\phi_2 - \phi_2'(t)\} + \{\phi_3 - \phi_3'(t)\} \\ + \{\Delta_1 - \Delta_1'(t)\} + \{\Delta_2 - \Delta_2'(t)\} + \{\Delta_3 - \Delta_3'(t)\}$$

In this manner, the duty  $t$  can be measured precisely.

Since the thickness of a resist varies due to exposure or development as is known in the art, there may be cases where use of the resist thickness  $d$  measured beforehand with respect to a portion having no pattern is inappropriate for calculation. In the present embodiment, measurement is made with use of plural wavelengths and this enables simultaneous measurement of the duty and the resist shape as well as the resist thickness at the pattern position.

Further, since the state of polarization varies with the film thickness, for determination of the duty as described, the thickness  $d$  may be added as a parameter for calculation, and the duty  $t$  and thickness  $d$  may be so determined that the following function becomes minimum:

$$D(t) = \{\phi_1 - \phi_1'(t, d)\} + \{\phi_2 - \phi_2'(t, d)\} + \{\phi_3 - \phi_3'(t, d)\} \\ + \{\Delta_1 - \Delta_1'(t, d)\} + \{\Delta_2 - \Delta_2'(t, d)\} + \{\Delta_3 - \Delta_3'(t, d)\}$$

In this manner, the shape of a sensitized pattern can be measured more exactly. When the shape of a resist is to be determined practically, in consideration of many parameters it is desirable to perform the measurement through detected values obtained with use of different incidence angles.

Similar advantageous result of measurement based on plural wavelengths of projected light is attainable with an arrangement wherein light from a halogen lamp is passed through a spectroscope and, by using an optical fiber, the light from an exit port of the spectroscope is directed to the light source means. Further, a light source which provides plural wavelengths such as a tunable laser or plural light source of different wavelengths may be used with similar advantageous result. The remaining portion of this embodiment has substantially the same structure as of the first embodiment.

#### [Eighth Embodiment]

An eighth embodiment of the present invention is an example wherein a light source projects light under a given incidence condition to a single sensitized pattern, and processing means calculates an optimum incidence condition on the basis of a detected value of a change in the light. Light source then projects light under the optimum incidence condition, to determine the state of formation of the sensitized pattern.

As described, the thickness of a resist varies due to exposure or development process, and it may cause an error of measurement. In consideration of this, measurement is made once under an optimum incidence condition as calculated on the basis of preparatively measured value related to the subject of measurement, such as refractivity  $n_s$  of the underlying substrate of the resist, refractivities  $n_1$  and  $n_2$  of unexposed and exposed portions of the resist, thickness  $d$ , the period, angle and number of lines of the exposed pattern, for example. Then, by comparing the result of measurement with calculated values, such a numerical value (e.g., thickness) which differs from an expected value largely is corrected, and optimum incidence condition is calculated again. The light source is then adjusted with respect to the renewed optimum incidence condition, and light is projected under it. A change in light is then detected by a light receiving system, whereby a resist pattern is measured.

The incidence condition here may be incidence angle, incidence direction or incidence wavelength.

[Ninth Embodiment]

Next, an embodiment of device manufacturing method which uses an exposure method described above, will be explained.

Figure 16 is a flow chart of procedure for manufacture of microdevices such as semiconductor chips (e.g. ICs or LSIs), liquid crystal panels, CCDs, thin film magnetic heads or micro-machines, for example. Step 1 is a design process for designing a circuit of a semiconductor device. Step 2 is a process for making a mask on the basis of the circuit pattern design. Step 3 is a process for preparing a wafer by using a material such as silicon. Step 4 is a wafer process which is called a pre-process wherein, by using the so prepared mask and wafer, circuits are practically formed on the wafer through lithography. Step 5 subsequent to this is an assembling step which is called a post-process wherein the wafer having been processed by step 4 is formed into semiconductor chips. This step includes assembling (dicing and bonding) process and packaging (chip sealing) process. Step 6 is an inspection step wherein operation check, durability check and so on for the semiconductor devices provided by step 5, are carried out. With these processes, semiconductor devices are completed and they are shipped (step 7).

Figure 17 is a flow chart showing details of the wafer process. Step 11 is an oxidation process for oxidizing the surface of a wafer. Step 12 is a CVD process for forming an insulating film on the wafer surface. Step 13 is an electrode forming process for forming electrodes upon the wafer by vapor deposition. Step 14 is an ion implanting process for implanting ions to the wafer. Step 15 is a resist process for applying a resist (photosensitive material) to the wafer. Step 16 is an exposure process for printing, by exposure, the circuit pattern of the mask on the wafer through the exposure apparatus described above. Step 17 is a developing process for developing the exposed wafer. Step 18 is an etching process for removing portions other than the developed resist image. Step 19 is a resist separation process for separating the resist material remaining on the wafer after being subjected to the etching process. By repeating these processes, circuit patterns are superposedly formed on the wafer.

With these processes, high density microdevices can be manufactured.

Next, another aspect of the present invention will be explained.

Here, an important feature of measurement method for measurement of a pattern formed on a substrate, will be explained.

An embodiment of the present invention is based on a principle that an average refractivity or effective value thereof of a pattern varies with a change in shape of the pattern.

More specifically, as a reticle (R), a mask with a pattern for process control, comprising a line-and-space pattern having a periodicity in one direction, for example, is used, and images of such reference pattern are printed sequentially onto a wafer (W).

Latent image in the resist material on the wafer defined through this exposure process (i.e., an image defined by a portion whose refractivity has been changed due to chemical change caused by exposure) or a protrusion-recess pattern (rectangular-wave-like pattern) on the wafer formed after a development process is then irradiated with input light from a light projecting means. Signal light from the pattern is received by light receiving means. By using a signal from the light receiving means, a change in input light (change in state of polarization of input light or change in intensity of it) are detected. On the basis of detection of a change in light corresponding to the light incidence condition, the state of formation of the pattern is detected through processing means.

Now, an example of such a change of light will be taken, with reference to a case where the state of polarization of input light changes, and measurement of a resist pattern on a wafer will be explained.

For a pattern, light having a predetermined wavelength and a predetermined state of polarization is projected on to a resist with a predetermined angle of incidence. The light is transmitted through the resist. The light is reflected by the surface of the wafer bottom substrate, and it is transmitted again through the resist. The light going out of the resist is combined with the light having been directly reflected by the surface of the resist. The state of polarization of such combined light is measured.

It is known that, for a protrusion-recess pattern phase type diffraction grating, no diffraction light is produced with a wavelength longer than the pitch thereof, and it has a double refraction characteristic.

In an embodiment of the present invention, description will be made mainly on a case where reflection light is detected. However, if the pitch of a resist pattern is larger than the wavelength, diffraction light is produced. Similar measurement is attainable with such diffraction light.

Now, a polarization analysis method used in the present invention will be explained.

It is now assumed that grating thickness is  $d$  and duty ratio (the ratio of a remaining resist portion to the period) is  $t$ , and also that laser light having a wavelength greater than the period is perpendicularly incident on a double refraction element. Here, it is known that, depending on whether the state of polarization of the input or projected light is parallel to or perpendicular to the grating groove, refractivities  $n_{||}$  and  $n_{\perp}$  in the periodic structure portion of the double refraction element are given by the following equations. When effective refractivity with respect to light parallel to the grating groove is  $n_{||}$ , and effective refractivity with respect to light perpendicular to the grating groove is  $n_{\perp}$ , then:

$$n_{||} = \sqrt{(t \cdot n_1^2 + (1-t) \cdot n_2^2)}$$

$$n_{\perp} = 1/\sqrt{((t/n_2^2) + (1-t)/n_1^2)}$$

where  $n_1$  and  $n_2$  are refractivities of the line portion and of the space portion of the grating. The line portion  $L$  and the space portion  $S$  are such that, for a case of resist latent image,  $L$  corresponds to a resist and  $S$  corresponds to an exposed resist. When the resist is developed,  $L$  corresponds to a resist and  $S$  corresponds to a gas such as an air.

The equations of refractivity mentioned above are approximation equations in a case where the period of the periodic structure is sufficiently small as compared with the wavelength. If the electric field is calculated exactly, the refractivity can be calculated also in a case where the period is the same as or similar to the wavelength or a case where a structure other than a periodic structure is used.

A model of polarization analysis corresponds to measurement double refractivity of a double refractivity medium of a predetermined thickness, on a wafer substrate. The polarization analysis method is such that rectilinearly polarized light having a zero P/S phase difference (between P-polarization and S-polarization) and having an amplitude ratio of 1 is projected upon a wafer substrate, such as above, with a predetermined angle  $\theta$ , and phase difference ( $\Delta$ ) and amplitude ratio ( $\phi$ ) of reflected light therefrom are measured, to thereby determine  $n_{||}$  and  $n_{\perp}$ . Then, from the refractivities  $n_1$  and  $n_2$  of the line portion  $L$  and of the space portion  $S$ , having been measured beforehand, and from the resist thickness  $d$ , the values of  $n_{||}$  and  $n_{\perp}$  are determined. Then, on the basis of the values  $n_{||}$  and  $n_{\perp}$  determined in accordance with the polarization analysis method described above, duty  $t$  is determined by use of the equation mentioned above or the equation solved exactly. Since such polarization analysis method is known in the art, description of details of it will be omitted.

As regards the light incidence condition (e.g., incidence angle, azimuth angle with respect to pattern direction, wavelength), optimum condition varies with the refractivity of resist, film thickness thereof or the shape of the pattern. The condition also varies for a developed resist pattern measurement and for a latent image resist pattern measurement. Further, for a latent image, since the difference in refractivity between an exposed portion and an unexposed portion is small, in order that a minute change to be produced in pattern shape with a small change in exposure condition is resolved and detected with a small change in light, measurement may be made with such incidence condition that a large change is produced in light with the pattern formation condition.

In an embodiment of the present invention, measurement is made to a photosensitive substrate on which a line-and-space pattern is formed, this being done prior to a development process. After the development process, measurement is made again, and results are compared with each other. On the basis of this, if there is produced a wafer with non-uniformness of pattern or with a pattern not having a predetermined shape, whether the cause is involved in the development process or not is discriminated.

#### [Tenth Embodiment]

Figure 18 is a schematic view of a main portion of a tenth embodiment of the present invention, and Figure 2 illustrates an example of a pattern.

This embodiment is an example wherein, as a change in projected light through a sensitized pattern, a change in state of polarization is taken and, based on it, any disorder of or failure in an exposure process and a development process can be detected separately.

Figure 19 illustrates a reference pattern 201p on the surface of a reticle. The reference pattern 201p comprises orthogonally arrayed line-and-space patterns 202 and 203 each being provided by lines ( $L$ ) and spaces ( $S$ ).

In this embodiment, the pattern 201p comprising line-and-space patterns 202 and 203 formed on the reticle is printed successively on a wafer 106, coated with a resist, in accordance with step-and-repeat method.

Figure 20 illustrates sections of a resist. Within a resist on the wafer 106 after it is exposed, there are latent images formed such as shown in Figure 20. The latent image is defined by a change in property of a resist resulting from a chemical change, for example, caused by irradiation with exposure light. Hatched portions depict exposed portions and, generally the refractivity has been changed in these portions. Reference numeral 305 in Figure 20 denotes a latent image as the exposure amount and focus amount (position of the wafer with respect to an optical axis direction of a projection lens), for example, are optimized. There is a pattern of a duty 0.5, formed. When the exposure amount changes, for example, if the exposure amount is less than a correct value, a latent image pattern of a duty not greater than 0.5 will be formed, such as at 304. If on the other hand the exposure amount is larger than a correct value, a latent image pattern of a duty not smaller than 0.5 will be formed, such as at 306.

Also, if the focus amount in the exposure process changes, there occurs a change in tilt of a side wall of the pattern, such as depicted at 302 or 308.

If the exposure condition in an exposure apparatus is optimized and the exposure process is performed while maintaining it constant, resultant patterns formed will have a constant shape. If any disorder occurs at this stage in the exposure apparatus, however, these latent images will have different shapes and thus results of measurement to the state of formation of the patterns will be different from each other.

Referring to Figure 18, the pattern measurement based on detection of a change in state of polarization, will be explained.

By means of a process monitoring system which comprises a light source portion 101, a light receiving portion 102, a driver 103, a polarization processing device 104, and a CPU 109 and which is based on a polarization analysis method, amplitude ratio  $\phi$  and phase difference  $\Delta$  of reflected light with respect to a projected light are measured, and state of formation of the pattern is discriminated.

Figure 21 is a schematic view wherein the light path in the Figure 18 arrangement is extended. In Figures 18 and 21, light source means (light projecting means) 101 comprises a light source 1011 (which may comprise a He-Ne laser or a semiconductor laser or, alternatively, monochromatic light from a spectrometer) and a polarization element 1012 such as a Glan-Thompson prism, for example. The polarization element 1012 has its polarization plane disposed at 45 deg. with respect to the sheet of the drawing, so that, with respect to the wafer 106, the same quantity of P-polarization component (parallel to the sheet of the drawing) and S-polarization component (perpendicular to the sheet of the drawing) are provided. Thus, the phase difference  $\Delta$  between these P-polarized light and S-polarized light is zero, and an amplitude ratio  $\phi$  is 1.

The light receiving portion (light receiving means) 102 comprises a quarter wave plate 1024 having its anisotropic axis perpendicular to the light 105, a polarization element (analyzer) 1022 such as a Glan-Thompson prism, for example, and a photoelectric converting element 1021. The quarter wave plate 1024 is held within a rotary mechanism 1023 having a rotational axis along the light 105 direction. It is rotatable at a constant speed in response to a signal from a driver 103.

Light 105 from the light source means 101 is reflected by the surface of a resist on the wafer 106 and by the surface of the wafer substrate. In combined light of these reflection lights, the phase difference  $\Delta$  and amplitude ratio  $\phi$  of P-polarized component and S-polarized component vary in accordance with the double refractivity  $n_1$  and  $n_2$ , for example, of the resist on the wafer 106.

This light is detected by the detector 1021, by way of the rotating quarter wave plate 1024 and analyzer 1022. The polarization processing device 104 produces an electric signal of sine wave corresponding to the phase difference  $\Delta$  and amplitude ratio  $\phi$ . Then, from positional information of sine wave of DC component magnitude and amplitude thereof, the phase difference  $\Delta$  and amplitude  $\phi$  are determined.

On the basis of polarization analysis method as described and when refractivity  $n_1$  of the unexposed portion of the resist, refractivity  $n_2$  of an exposed portion thereof, thickness  $d$  of the resist, and complex refractivity  $n_s$  of the substrate, having been measured beforehand, are given, the CPU 109 calculates  $n_L$  with the line-and-space resist pattern taken as a double refractivity structure. Further, the duty  $t_L$  is determined from the value  $n_L$ , and in accordance with the following equation:

$$t_L = n_1^2 \cdot (n_2^2 - n_L^2) / (n_L^2 \cdot (n_2^2 - n_1^2))$$

From the value of refractivity  $n_{II}$ , the duty  $t_{II}$  is given by:

$$t_{II} = (n_{II}^2 - n_2^2) / (n_1^2 - n_2^2)$$

By averaging these two values, the precision can be improved, that is:

$$t_1 = (t_L + t_{II}) / 2$$

Generally, the duty  $t$  can be determined with the procedure described above. However, because of a possibility of variation in measured value due to resist non-uniformness or underlying structure, as shown in a plan view of Figure 22, to polarization analysis measurement in X direction, a second polarization analysis system in Y direction perpendicular to it is provided to perform simultaneous measurement at substantially the same measurement point as measured by the first polarization analysis system (101, 102). The precision can be improved thereby, as follows:

Also in this case, similarly to determination of duty  $t_1$ :

$$t_2 = (t_L + t_H)/2$$

By using duty  $t_1$  described hereinbefore, an average is calculated:

$$t = (t_1 + t_2)/2$$

The measurement precision for duty  $t$  thus increases.

In order for enhanced precision for latent image pattern measurement, a duty obtained through polarization analysis of lines and spaces of a desired pattern and a value of measurement made to a developed sample with use of a scanning electron microscope may be compared with each other to determine an offset for duty resulting from an underlying structure in the polarization analysis method. In the subsequent measurements, a value from which the offset is subtracted may be used as a correct measured value. As regards a pattern after development, with comparison of the duty obtained through polarization analysis with a measured value, any offset which depends on the process can be removed. The comparison with use of scanning electron microscope may be done only once in the initial stage when the condition such as process changes, and it is not necessary during the procedure after that.

Referring now to Figure 23, the operation of a process monitoring system which is based on detection of a change in state of polarization, will be explained.

Figure 23 is a flow chart of procedure for a development process monitoring.

A wafer after an exposure step 601 is conveyed to a process monitor, and at 602 the polarization processing system 104 detects a phase difference  $\Delta$  and an amplitude ratio  $\phi$ , this being made to a latent image as described hereinbefore. On the basis of the detected phase difference  $\Delta$  and amplitude ratio  $\phi$  and of comparison of results of measurement to plural patterns on the wafer, the CPU 109 discriminates whether the patterns in plural shots on the wafer have been formed with a shape within a preset tolerable range. If the state of formation of the pattern is out of the tolerable range, at step 604 the shot in which defective pattern is formed is memorized as E. Reference numeral 610 denotes positions of defective shots on the wafer by E. If all the patterns have been formed in satisfactory state of formation, the wafer is directly conveyed to a development step 605. Also in cases where there is a defective shot, after step 604 the wafer is conveyed to step 605.

A wafer having been processed by the development step 605 is again conveyed to the process monitor and, at step 606, measurement is made to plural patterns on the wafer. Here, for measurement of the state of formation of a resist pattern after development, measurement condition (such as incidence angle or wavelength of projected light) and constant (such as refractivity or thickness) necessary for determination of the state of formation are different from those for the latent image pattern measurement. The method of measurement is essentially the same as the one described hereinbefore. In the case of a developed pattern, spaces of a line-and-space pattern correspond to a refractivity of a gas such as an air. At step 607, the CPU 109 discriminates whether patterns in plural shots on the wafer have formed uniformly with a shape within a preset tolerable range, this being made on the basis of comparison with the results of measurement made to plural patterns on the wafer. If the state of formation of a pattern is out of the tolerable range, the shot in which a defective pattern is formed is memorized as D. Reference numeral 616 denotes positions of defective shots produced during the development process, at D. If all the patterns are in satisfactory range of state of formation, it is concluded that patterns are formed with no disorder in the development process, and the wafer is conveyed directly to a subsequent step 611.

If there is a defective shot, the procedure goes to step 609, and the CPU 109 compares the positions of shots E for which non-uniformness of pattern before the development process has been memorized, with positions of shots D for which non-uniformness of pattern after development process. If they are coincident with each other, the non-uniformness, that is, the formation of defective pattern is attributable only to the exposure process. Thus, it is concluded that a disorder is involved in the exposure step, and an alarm is given to an operator. If the positions are not coincident with each other, at step 610, discrimination is made as to whether there is any E shot or not. If there is any E, failure of uniform shot may be attributed to both the exposure process and the development process. Thus, it is concluded that both of these processes involve disorder, and an alarm is given to the operator. If there is no E, it is concluded that any disorder is involved only in the development process, and a corresponding alarm is given to the operator.

In the present embodiment as described above, if there is defectiveness in pattern formation, whether it has been caused in the exposure process or in the development process is detected separately as illustrated in Figure 23. Further, when a disorder occurs in respective processes, an alarm is given so that the operator can meet the problem promptly.

Referring to Figure 24, a tolerable range for pattern measurement will be explained. This is one method for preparing, as initial data for process monitoring in this embodiment, such data which is to be possessed by the process monitor. Figure 24 shows an example wherein, to a single wafer, shot exposures of 8x6 are performed while successively changing by a small amount the exposure amount along one direction and the focus amount along a direction

perpendicular to it, wherein results of polarization analysis at points 8x6 before development process are illustrated in  $\Delta$ - $\phi$  map. For example, as regards measurement points along a line 710, the exposure amount is kept constant while the focus varies. On the other hand, as regards measurement points along a line 701, the focus is kept constant while the exposure amount varies.

As regards these points 8x6, by taking correlation with scanning electron microscope measurement after the development process as described, a range of optimum duty can be specified as a rectangular frame AX in the  $\Delta$ - $\phi$  map before the development process. Similarly, by taking correlation between the results of polarization analysis after development and scanning electron microscope measurement, a range of optimum duty can be specified also as a rectangular frame AX in the  $\Delta$ - $\phi$  map after development process. As a matter of course, the rectangular frame in the  $\Delta$ - $\phi$  map for optimum duty is different, before and after the development process. Thus, the CPU 109 of the process monitoring system measures the exposed shots by polarization analysis method and, if  $\Delta$  and  $\phi$  are within this frame AX, it is concluded that they are within a tolerable range, representing an optimum duty. In association with each of processes, the data for rectangular frame of optimum duty in the  $\Delta$ - $\phi$  map be stored in the apparatus. In that occasion, pattern comparison may be made without using values of duty  $t$  or the like, but direct comparison may be made with use of measured data such as  $\Delta$  and  $\phi$ , for example, before calculation. This effectively saves calculation time.

In this embodiment as described above, if any disorder occurs in the exposure process and/or the development process, the occurrence of such disorder in either process can be detected separately and promptly. Thus, it contributes to increases in yield of device mass-production procedure.

#### [Eleventh Embodiment]

An eleventh embodiment of the present invention is an example wherein an etching process is to be monitored. The etching process is a step in which, by using a resist having been developed as a mask, uncovered portions of a substrate are removed (etched) whereby a resist pattern is transferred to the substrate.

The pattern measurement is made essentially in the same method as of the tenth embodiment. However, since as regards the pattern after the etching process, there is a resist pattern which overlaps with the pattern of the substrate, two layers of double refraction films are present. Further, if the substrate is not a dielectric material such as a silicon substrate, there will be absorption by the substrate material. Thus, calculation of pattern based on polarization analysis becomes complexed. Since in the etching process the linewidth of a resist pattern can be processed with good precision, there are cases where etching depth monitoring is desired. In such cases, since the duty or the linewidth of a resist pattern as measured before the etching process corresponds to the duty or the linewidth of the pattern of the substrate, they may be taken as known values. Thus, by detecting the thickness of double refraction layer provided by the substrate pattern on the basis of polarization analysis, the etching depth can be detected exactly.

Figure 25 is a flow chart of the process monitoring procedure.

First, a wafer after a development process 801 is conveyed to a process monitor, and at step 802, the polarization processing system 104 detects a phase difference  $\Delta$  and an amplitude ratio  $\phi$ , this being done to a latent image as described. Then, on the basis of the detected phase difference  $\Delta$  and amplitude ratio  $\phi$ , the CPU 109 measures the state of formation of the pattern. At step 803, from the comparison of the results of measurement to plural patterns on the wafer, the CPU 109 discriminates whether the patterns in plural shots on the wafer have been formed with a shape within a preset tolerable range or not. Alternatively, as described, discrimination may be made as to whether the phase difference  $\Delta$  and the amplitude ratio  $\phi$  detected are within a rectangular frame AX on the  $\Delta$ - $\phi$  map of optimum duty. If the state of formation of a pattern is out of the tolerable range, at step 804 the shot having a defective pattern formed is memorized as E. Reference numeral 815 denotes positions of defective shots on the wafer, at E. If all the patterns are in the satisfactory state of formation, the wafer is conveyed directly to an etching step 805. If there is a defective shot, the wafer is conveyed after step 804 to the etching step 805.

A wafer having been processed by the etching step 805 is again conveyed to the process monitor and, at step 806, measurement is made to plural patterns on the wafer. Here, for measurement of the state of formation of a resist pattern after the etching process, measurement condition (such as incidence angle or wavelength of projected light) and constant (such as refractivity or thickness) necessary for determination of the state of formation are different from those for the latent image pattern measurement. The method of measurement is essentially the same as the one described hereinbefore. At step 807, the CPU 109 discriminates whether patterns in plural shots on the wafer have formed uniformly with a shape within a preset tolerable range, this being made on the basis of comparison with the results of measurement made to plural patterns on the wafer. If the state of formation of a pattern is out of the tolerable range, the shot in which a defective pattern is formed is memorized as D, at step 808. Reference numeral 816 denotes positions of defective shots produced during the development process, at D. If all the patterns are in satisfactory range of state of formation, it is concluded that patterns are formed with no disorder in the development process, and the wafer is conveyed directly to a subsequent step 811.

If there is a defective shot, the procedure goes to step 809, and the CPU 109 compares the positions of shots E

for which non-uniformness of pattern before the etching process has been memorized, with positions of shots D for which non-uniformness of pattern after the etching process. If they are coincident with each other, the non-uniformness, that is, the formation of defective pattern is attributable only to the development process. Thus, it is concluded that a disorder is involved in the development step, and an alarm is given to an operator. If the positions are not coincident with each other, at step 810, discrimination is made as to whether there is any E shot or not. If there is any E, failure of uniform shot may be attributed to both the development process and the etching process. Thus, it is concluded that both of these processes involve disorder, and an alarm is given to the operator. If there is no E, it is concluded that any disorder is involved only in the etching process, and a corresponding alarm is given to the operator.

In this embodiment as described above, if any disorder occurs in the pattern formation, whether it is attributable to a process before the etching process or to the etching process can be detected separately, as shown in Figure 8. Also, when a disorder occurs in respective processes, an alarm is given to an operator so that the operator can meet the problem promptly. Thus, it contributes to increases in yield of device mass-production procedure.

#### [Twelfth Embodiment]

A twelfth embodiment of the present invention is an example where an ashing process is to be monitored. The ashing process is a step for removing a resist after an etching process to uncover the substrate pattern, and it is a simple and final process in pattern formation.

The pattern measurement is made essentially in the same manner as of the tenth embodiment.

Figure 26 is a flow chart of the process monitoring procedure.

First, a wafer after an etching process 901 is conveyed to a process monitor, and at step 902, the polarization processing system 104 detects a phase difference  $\Delta$  and an amplitude ratio  $\phi$  with respect to a pattern defined by the resist and substrate of the wafer. Then, on the basis of the detected phase difference  $\Delta$  and amplitude ratio  $\phi$ , the CPU 109 measures the state of formation of the pattern. At step 903, from the comparison of the results of measurement to plural patterns on the wafer, the CPU 109 discriminates whether the patterns in plural shots on the wafer have been formed with a shape within a preset tolerable range or not. If the state of formation of a pattern is out of the tolerable range, at step 904 the shot having a defective pattern formed is memorized as E. Reference numeral 915 denotes positions of defective shots on the wafer, at E. If all the patterns are in the satisfactory state of formation, the wafer is conveyed directly to an ashing step 905. If there is a defective shot, the wafer is conveyed after step 904 to the etching step 905.

A wafer having been processed by the ashing step 905 is again conveyed to the process monitor and, at step 906, measurement is made to plural patterns on the wafer. Here, for measurement of the state of formation of a resist pattern after the ashing process, measurement condition (such as incidence angle or wavelength of projected light) and constant (such as refractivity or thickness) necessary for determination of the state of formation are different from those for measurement of a pattern defined by a resist and substrate material. The method of measurement is essentially the same as the one described hereinbefore. At step 907, the CPU 109 discriminates whether patterns in plural shots on the wafer have formed uniformly with a shape within a preset tolerable range, this being made on the basis of comparison with the results of measurement made to plural patterns on the wafer. If the state of formation of a pattern is out of the tolerable range, the shot in which a defective pattern is formed is memorized as D, at step 908. Reference numeral 916 denotes positions of defective shots produced during the ashing process, at D. If all the patterns are in satisfactory range of state of formation, it is concluded that patterns are formed with no disorder in the ashing process, and the wafer is conveyed directly to a subsequent step 911.

If there is a defective shot, the procedure goes to step 909, and the CPU 109 compares the positions of shots E for which non-uniformness of pattern before the ashing process has been memorized, with positions of shots D for which non-uniformness of pattern after the ashing process. If they are coincident with each other, the non-uniformness, that is, the formation of defective pattern is attributable only to the etching process. Thus, it is concluded that a disorder is involved in the etching step, and an alarm is given to an operator. If the positions are not coincident with each other, at step 910, discrimination is made as to whether there is any E shot or not. If there is any E, failure of uniform shot may be attributed to both the etching process and the ashing process. Thus, it is concluded that both of these processes involve disorder, and an alarm is given to the operator. If there is no E, it is concluded that any disorder is involved only in the ashing process, and a corresponding alarm is given to the operator.

In this embodiment as described above, if any disorder occurs in the pattern formation, whether it is attributable to a process before the ashing process or to the ashing process can be detected separately, as shown in Figure 9. Also, when a disorder occurs in respective processes, an alarm is given to an operator so that the operator can meet the problem promptly. Thus, it contributes to increases in yield of device mass-production procedure.

## [Thirteenth Embodiment]

A thirteenth embodiment of the present invention is an example wherein a process monitor is arranged for universal use. In this embodiment, measurement condition and tolerable range for pattern shape, for example, may be inputted  
 5 beforehand and, by doing so, the system can meet any process. The embodiment will be explained in detail with reference to Figure 27.

Figure 27 is a flow chart of a process monitoring procedure. In this embodiment, pattern measurement is made before and after a given process B, by which whether any disorder has occurred before the process B or in the process B can be discriminated separately. After completion of a process A and before the process B, pattern measurement is  
 10 performed. The measurement is made essentially in the same manner as the preceding embodiment. That is, light is projected to a pattern, and a change in reflection light is detected, whereby the shape of the pattern is measured. Here, since the measurement condition (incidence angle or incidence wavelength, for example) and constant (refractivity or thickness, for example) necessary for determination of the state of formation, are variable with the process, measurement may be made on the basis of the condition for measurement before the process B, having been stored. Also,  
 15 as regards the constant for determination of state of formation, those having been stored are used.

At step 1003, from comparison of results of measurement to patterns on a wafer, the CPU 109 discriminates whether patterns in plural shots on the wafer have been formed uniformly and with a shape within a preset tolerable range. If the state of formation of a pattern is out of the tolerable range, it is concluded that any disorder is involved before the process B, and an alarm is given to an operator, at step 1004. If there is no disorder, the wafer is simply  
 20 conveyed to the process B, at step 1005.

At step 1006, pattern measurement is repeated again. Here, the measurement condition and constants having been stored in relation to the measurement after the process B, are used. At step 1007, from comparison of results of measurement made to patterns in plural shots on the wafer, discrimination is made as to whether patterns in plural shots of the wafer have been formed uniformly and with a shape within a tolerable range.

25 If the state of formation of a pattern is out of the tolerable range, it is concluded that a disorder has occurred in the process B, and a corresponding alarm is given to the operator, at step 1008. If there is no disorder, the wafer is simply conveyed to the process C at step 1009.

The process monitor according to the present embodiment is arranged for universal use, by which, as described above, if any disorder occurs before or after a particular process, whether the disorder has occurred in either before or after that process can be detected separately. Further, when the process monitor of the present embodiment is used for every process (before and after that), any disorder occurred in any process can be detected promptly. Also, when a disorder occurs in any process, an alarm is given to an operator so that the operator can meet the problem promptly. Thus, it contributes to increases in yield of device mass-production procedure.

35 While the invention has been described with reference to the structures disclosed herein, it is not confined to the details set forth and this application is intended to cover such modifications or changes as may come within the scope of the following claims.

## Claims

- 40 1. A pattern inspection system for detecting a state of a pattern formed on an object, said system comprising:

light projecting means for projecting input light on to a sensitized pattern defined on the object;  
 light receiving means for receiving signal light from the sensitized pattern;  
 45 processing means for detecting a change in the light by use of a signal from said light receiving means to detect the state of formation of the sensitized pattern; and  
 control means for changing a condition of incidence of light from said light projecting means.

- 50 2. A system according to Claim 1, wherein said light projecting means projects input light with different conditions of light incidence, and wherein said processing means detects the state of formation of the sensitized pattern on the basis of a change in light under the different conditions of light incidence.

- 55 3. A system according to Claim 1, wherein said light projecting means projects input light with different conditions of light incidence, wherein said processing means determines a condition of light incidence on the basis of a change in light under the different conditions of light incidence, and wherein said processing means detects the state of formation of the sensitized pattern when said light projecting means projects input light with the condition as determined.

4. A system according to Claim 1, wherein the condition of light incidence comprises an incidence angle of input light.
5. A system according to Claim 1, wherein the condition of light incidence comprises an incidence azimuth angle defined between a direction of the sensitized pattern and a plane of incidence.
- 5 6. A system according to Claim 1, wherein the condition of light incidence comprises a wavelength of input light.
7. A system according to Claim 1, wherein the state of formation of the sensitized pattern relates to a duty of the sensitized pattern.
- 10 8. A system according to Claim 1, wherein the state of formation of the sensitized pattern relates to a sectional shape of the sensitized pattern.
9. A system according to Claim 1, wherein the change in input light comprises a change in state of polarization of the input light.
- 15 10. A system according to Claim 1, wherein the change in input light comprises a change in intensity of the input light.
11. A system according to Claim 1, wherein the sensitized pattern comprises a latent image pattern before a developing process.
- 20 12. A system according to Claim 1, wherein the sensitized pattern comprises a developed pattern after a developing process.
- 25 13. A projection exposure apparatus for projecting a pattern of a first object, as illuminated with exposure light, on to a second object coated with a photosensitive material through a projection optical system to thereby form a sensitized pattern on the second object, said apparatus comprising:
  - 30 light projecting means for projecting input light on to the sensitized pattern with different conditions of light incidence;
  - light receiving means for receiving signal light from the sensitized pattern; and
  - processing means for detecting a change in the input light by use of a signal from said light receiving means to detect the state of formation of the sensitized pattern.
- 35 14. An apparatus according to Claim 13, wherein said light projecting means projects input light with different conditions of light incidence, and wherein said processing means detects the state of formation of the sensitized pattern on the basis of a change in light under the different conditions of light incidence.
- 40 15. An apparatus according to Claim 13, wherein said light projecting means projects input light with different conditions of light incidence, wherein said processing means determines a condition of light incidence on the basis of a change in light under the different conditions of light incidence, and wherein said processing means detects the state of formation of the sensitized pattern when said light projecting means projects input light with the condition as determined.
- 45 16. An apparatus according to Claim 13, wherein the condition of light incidence comprises an incidence angle of input light.
17. An apparatus according to Claim 13, wherein the condition of light incidence comprises an incidence azimuth angle defined between a direction of the sensitized pattern and a plane of incidence.
- 50 18. An apparatus according to Claim 13, wherein the condition of light incidence comprises a wavelength of input light.
19. An apparatus according to Claim 13, wherein the state of formation of the sensitized pattern relates to a duty of the sensitized pattern.
- 55 20. An apparatus according to Claim 13, wherein the state of formation of the sensitized pattern relates to a sectional shape of the sensitized pattern.

21. An apparatus according to Claim 13, wherein the change in input light comprises a change in state of polarization of the input light.
- 5 22. An apparatus according to Claim 13, wherein the change in input light comprises a change in intensity of the input light.
23. An apparatus according to Claim 13, wherein the sensitized pattern comprises a latent image pattern before a developing process.
- 10 24. An apparatus according to Claim 13, wherein the sensitized pattern comprises a developed pattern after a developing process.
- 15 25. A projection exposure method for projecting for projecting a pattern of a first object on to a second object coated with a photosensitive material through a projection optical system, said method comprising the steps of:
- illuminating the pattern of the first object with exposure light while changing an exposure condition and projecting the pattern of the first object so illuminated on to the second object, whereby a plurality of sensitized patterns are formed on the second object;
- 20 projecting input light from light projecting means to the sensitized patterns under different conditions of light incidence;
- receiving, through light receiving means, signal light from the sensitized patterns;
- detecting a change in input light by use of a signal from the light receiving means to detect a state of formation of the sensitized patterns through processing means; and
- 25 controlling exposure condition of the second object through control means, on the basis of a signal from the processing means.
26. A method according to Claim 25, wherein the state of formation of the sensitized patterns is detected through the processing means on the basis of a change in light under the different conditions of light incidence.
- 30 27. A method according to Claim 25, wherein the condition of incidence is determined through the processing means on the basis of a change in light under different conditions of light incidence, and wherein the state of formation of the sensitized patterns is detected as the light projecting means project input light with the thus determined condition of light incidence.
- 35 28. A method according to Claim 25, wherein the condition of light incidence comprises an incidence angle of input light.
29. A method according to Claim 25, wherein the condition of light incidence comprises an incidence azimuth angle defined between a direction of the sensitized pattern and a plane of incidence.
- 40 30. A method according to Claim 25, wherein the condition of light incidence comprises a wavelength of input light.
31. A method according to Claim 25, wherein the exposure condition relates to the amount of exposure upon the second object.
- 45 32. A method according to Claim 25, wherein the exposure condition relates to the position of the surface of the second object with respect to a direction of an optical axis of the projection optical system.
33. A method according to Claim 25, wherein the state of formation of the sensitized pattern relates to a duty of the sensitized pattern.
- 50 34. A method according to Claim 25, wherein the state of formation of the sensitized pattern relates to a sectional shape of the sensitized pattern.
35. A method according to Claim 25, wherein the change in input light comprises a change in state of polarization of the input light.
- 55 36. A method according to Claim 25, wherein the change in input light comprises a change in intensity of the input light.

37. A method according to Claim 25, wherein the sensitized pattern comprises a latent image pattern before a developing process.

38. A method according to Claim 25, wherein the sensitized pattern comprises a developed pattern after a developing process.

39. A substrate processing procedure monitoring system, comprising:

light projecting means for projecting input light on to a pattern defined on a substrate;

light receiving means for receiving signal light from the pattern;

detecting means for detecting a change in input light by use of a signal from said light receiving means; and

processing means having inspecting means for detecting a state of formation of the pattern on the basis of detection by said detecting means, for memorizing and comparing results of detection of the state of formation of the pattern before and after the processing procedure to the substrate.

40. A system according to Claim 39, wherein the change in input light comprises a change in a state of polarization of the input light.

41. A system according to Claim 39, wherein the change in input light comprises a change in intensity of the input light.

42. A system according to Claim 39, wherein said processing means discriminates a fault in the processing procedure, on the basis of the result of comparison.

43. A system according to Claim 39, wherein said processing means discriminates whether the change in input light is within a predetermined range and discriminates whether the state of formation of the pattern is satisfactory or not.

44. A system according to Claim 43, wherein, for discrimination of satisfactoriness of the state of formation of the pattern before and after the substrate processing procedure, there are different ranges as the predetermined range.

45. A system according to Claim 39, wherein there are plural patterns formed on the substrate, and wherein said processing means memorizes and compares, for each pattern, the results of detection of the state of formation of that pattern before and after the substrate processing procedure.

46. A system according to Claim 39, wherein the substrate processing procedure comprises one of a developing process, an etching process and an ashing process.

47. A substrate processing procedure monitoring method, comprising the steps of:

projecting input light on to a periodic pattern defined on a substrate;

receiving, through light receiving means, signal light from the pattern;

detecting a change in input light by use of a signal from the light receiving means;

detecting a state of formation of the pattern on the basis of detection at said detecting step; and  
memorizing and comparing results of detection of the state of formation of the pattern before and after the processing procedure to the substrate.

48. A method according to Claim 47, wherein the change in input light comprises a change in a state of polarization of the input light.

49. A method according to Claim 47, wherein the change in input light comprises a change in intensity of the input light.

50. A method according to Claim 47, wherein said processing step is effective to discriminate a fault in the processing procedure, on the basis of the result of comparison.

51. A method according to Claim 47, wherein said processing step is effective to discriminate whether the change in input light is within a predetermined range and to discriminate whether the state of formation of the pattern is satisfactory or not.

52. A method according to Claim 51, wherein, for discrimination of satisfactoriness of the state of formation of the

pattern before and after the substrate processing procedure, there are different ranges as the predetermined range.

53. A method according to Claim 47, wherein there are plural patterns formed on the substrate, and wherein said processing step is effective to memorize and compare, for each pattern, the results of detection of the state of formation of that pattern before and after the substrate processing procedure.

54. A method according to Claim 47, wherein the substrate processing procedure comprises one of a developing process, an etching process and an ashing process.

55. A method of manufacturing semiconductor devices comprising the method of any one of claims 25 to 38, wherein said second object comprises a wafer; and the step of fabricating a semiconductor device using the patterned wafer.

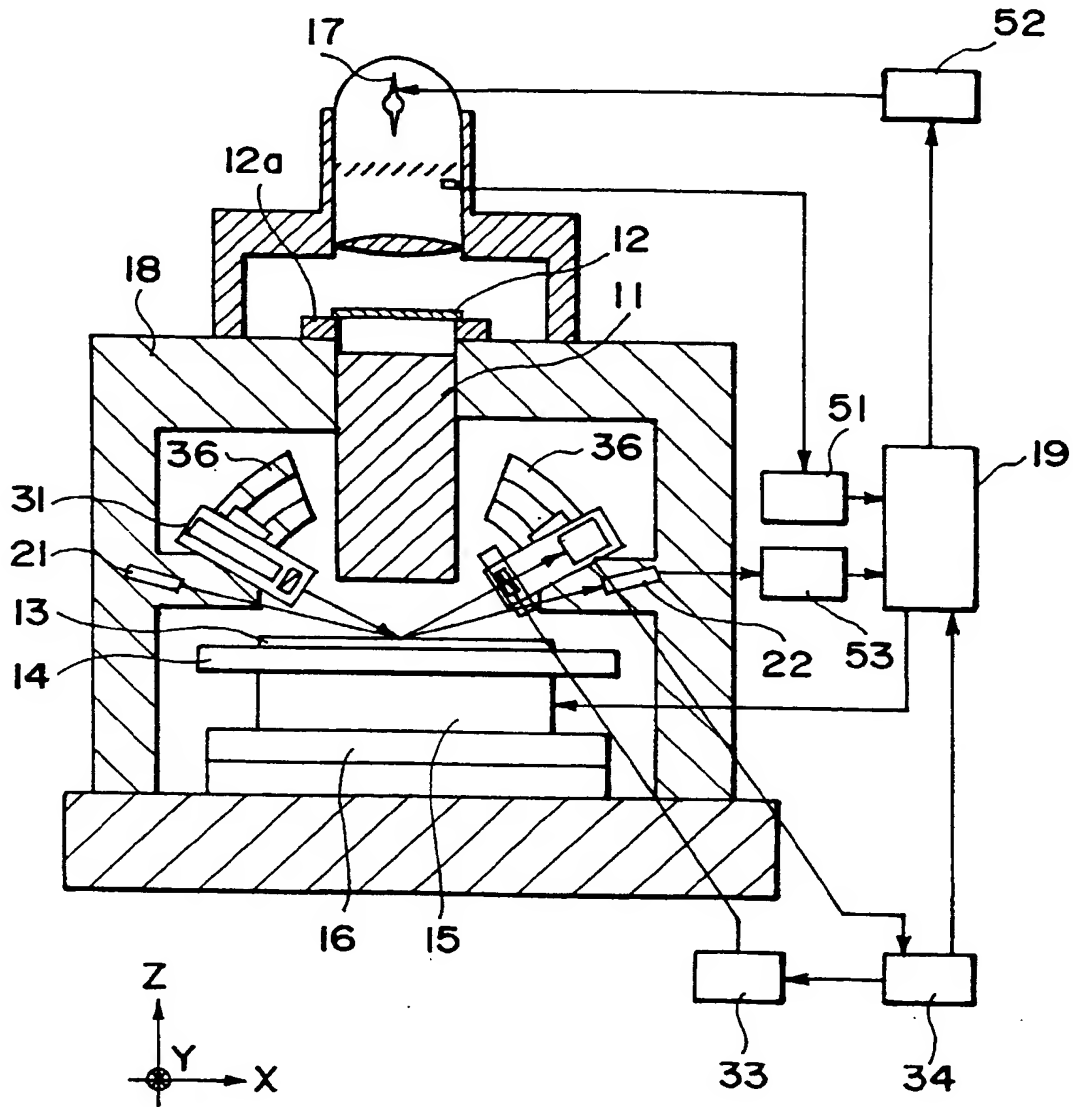


FIG. 1

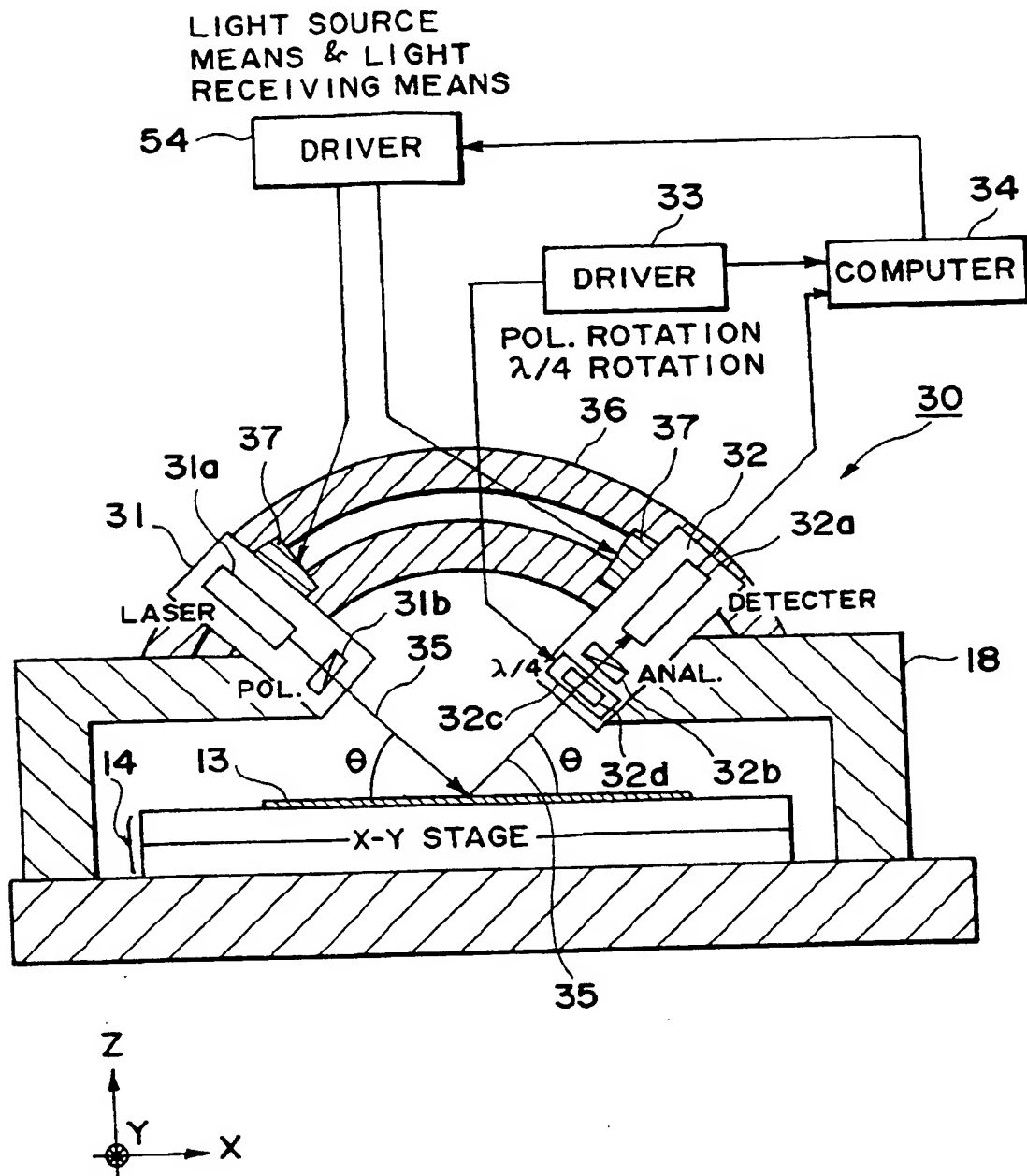


FIG. 2

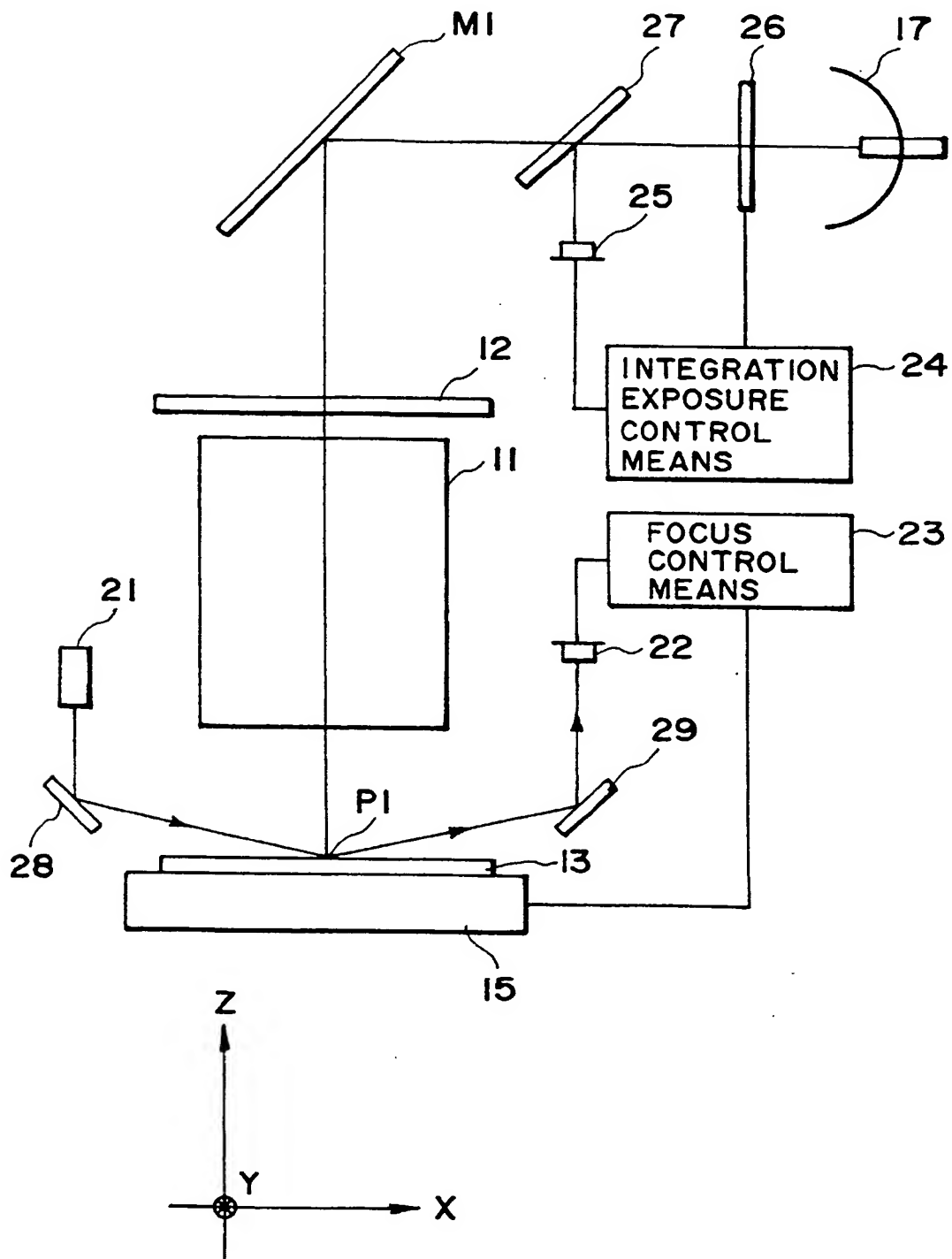


FIG. 3

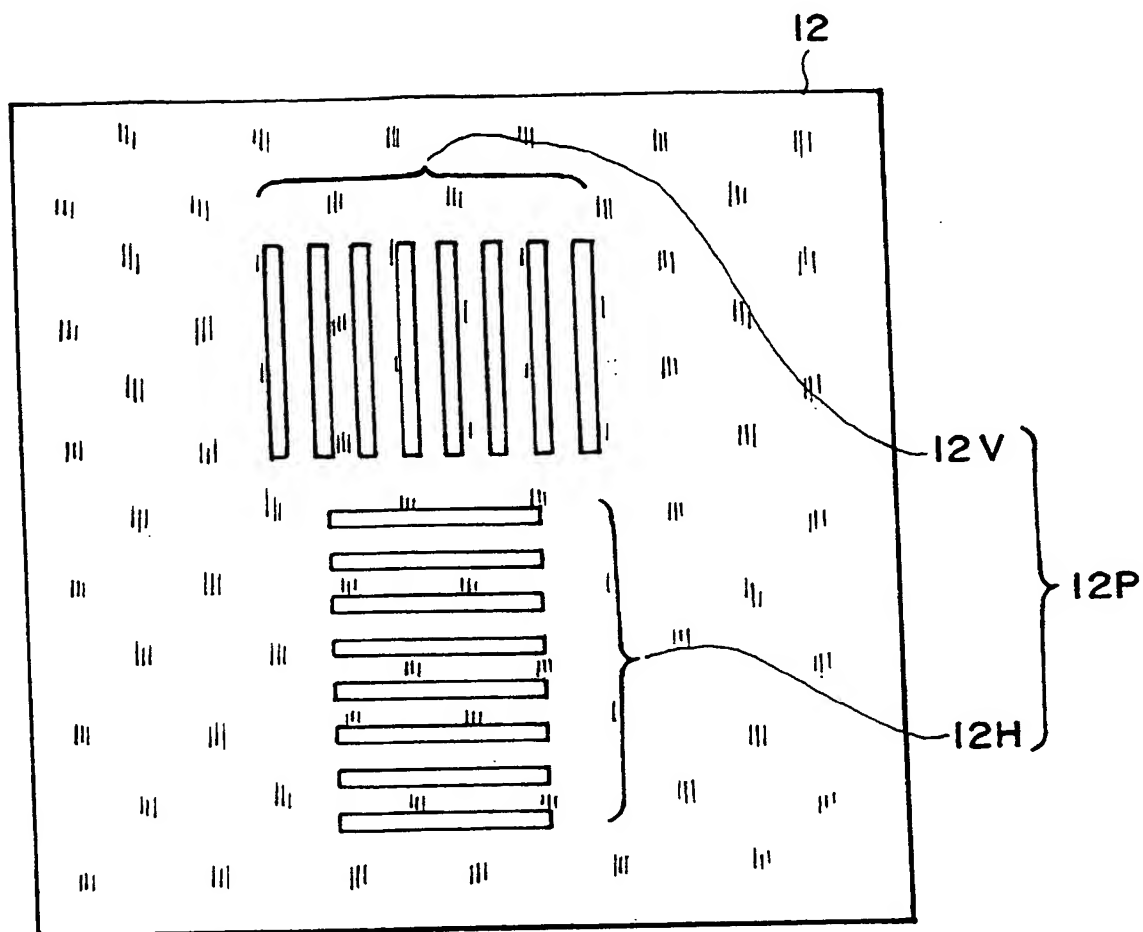


FIG. 4

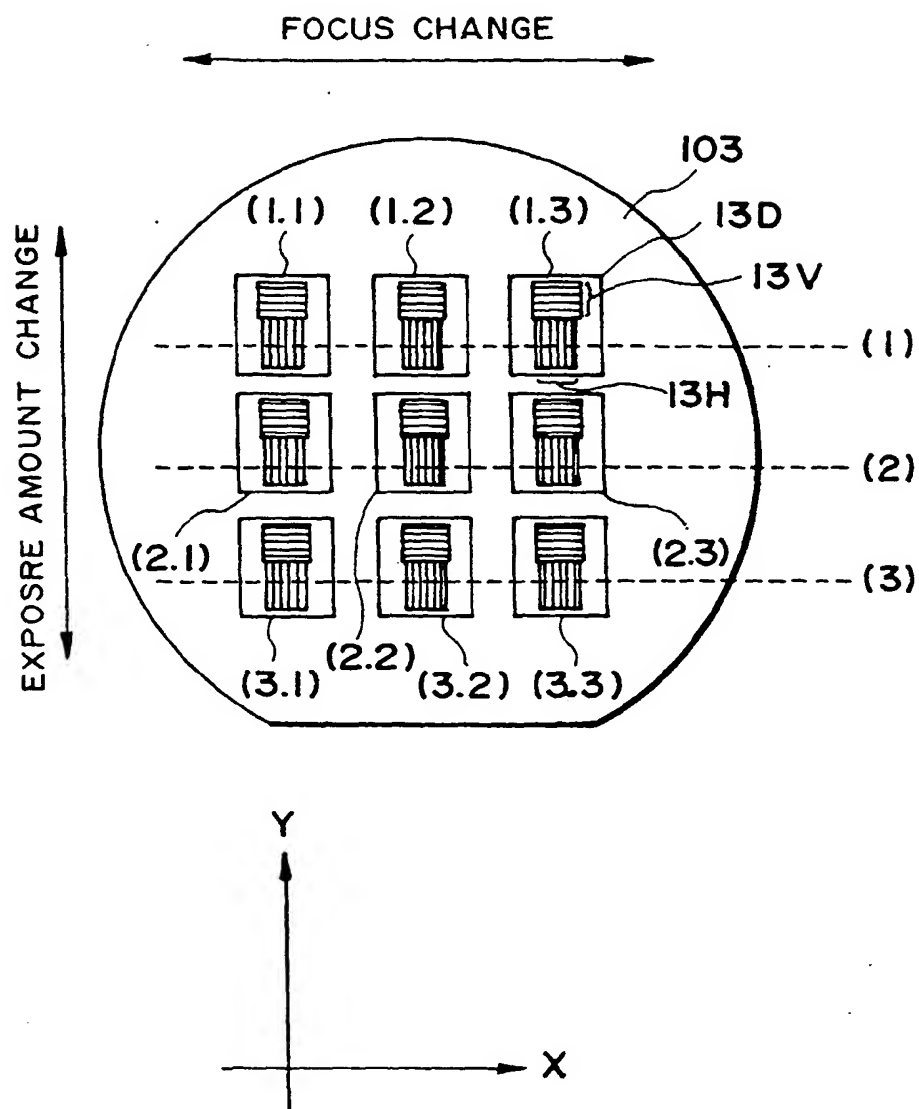
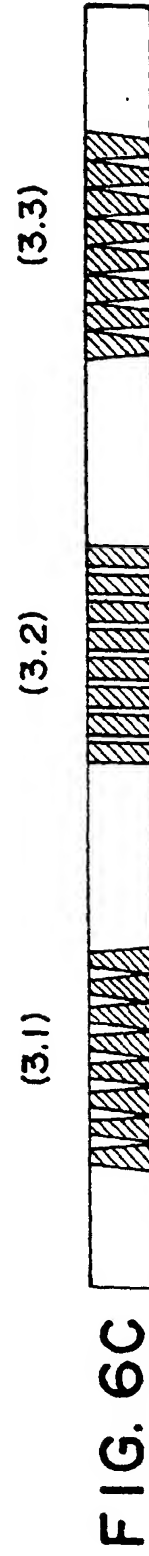
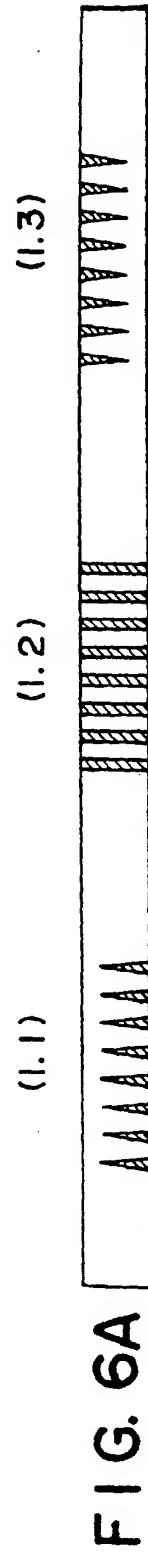


FIG. 5



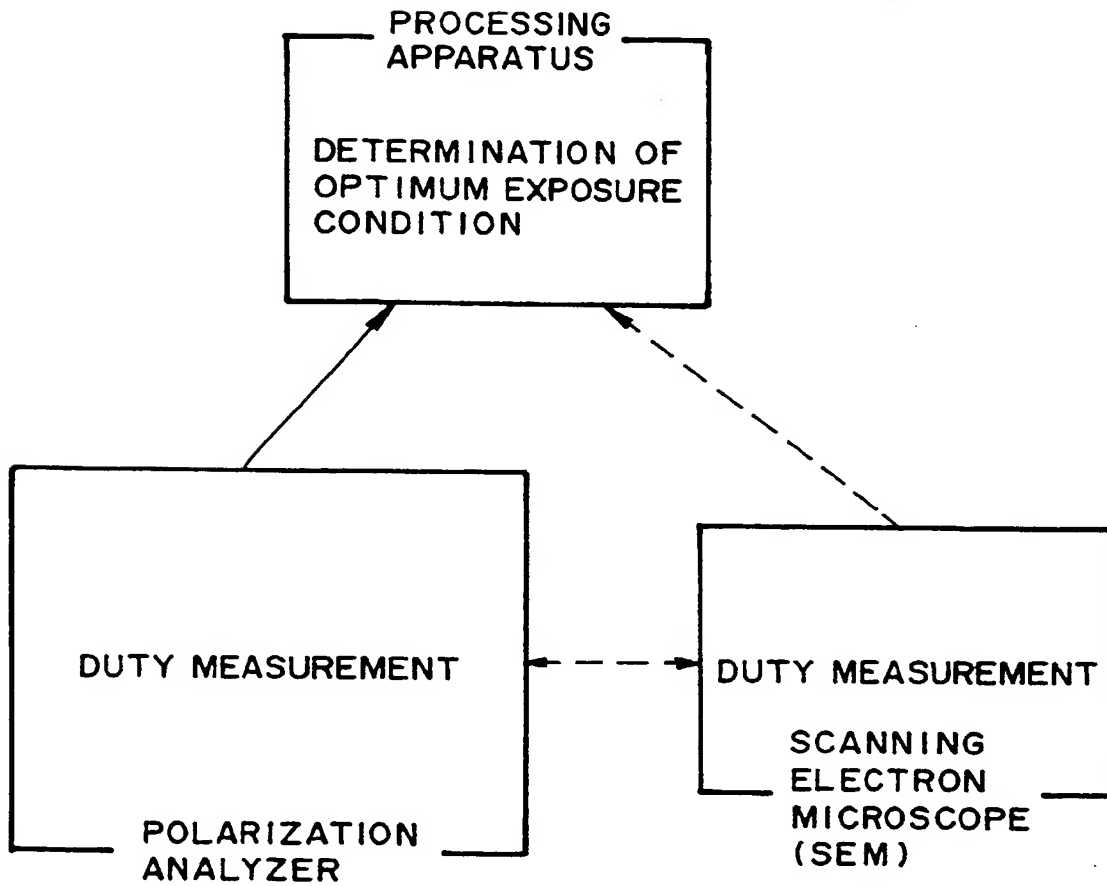


FIG. 7

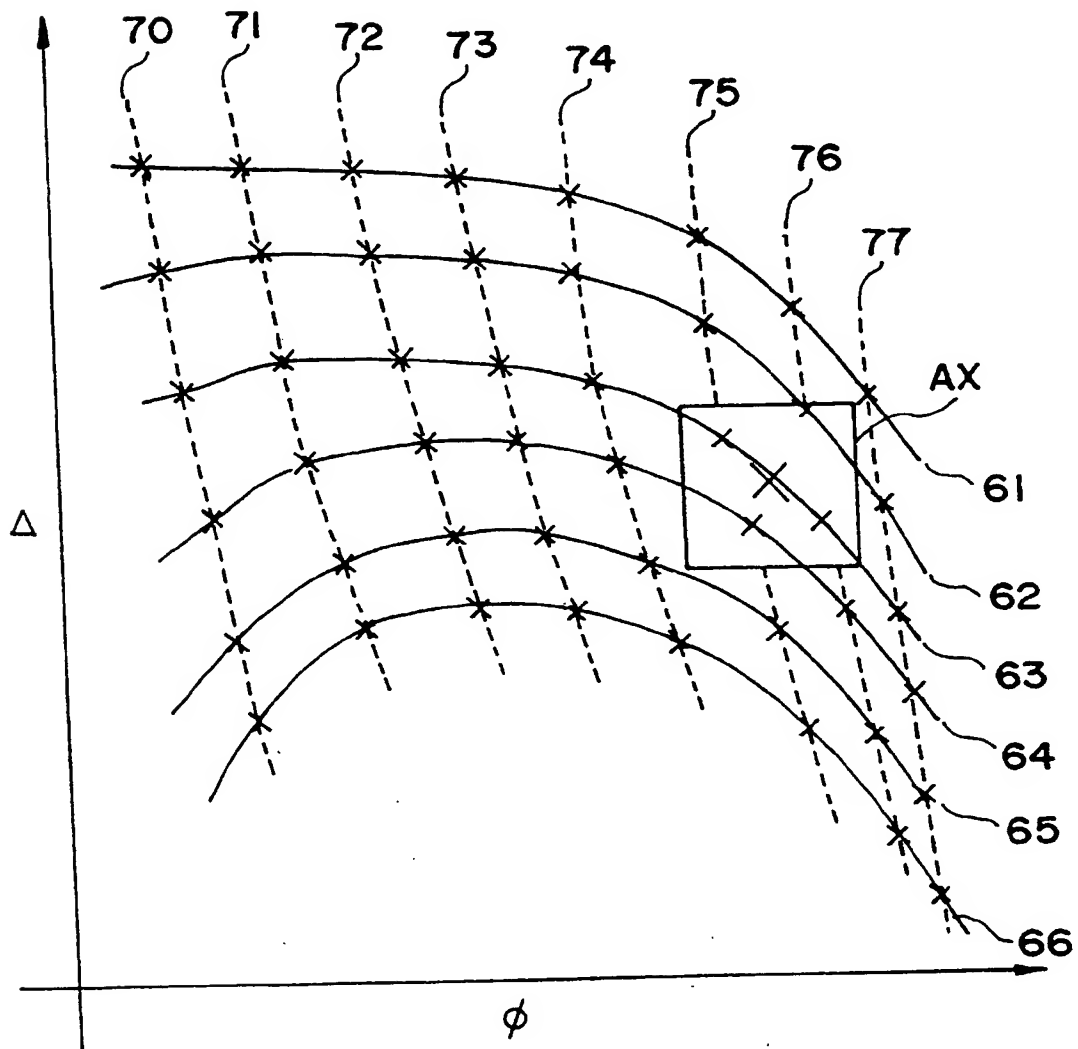


FIG. 8

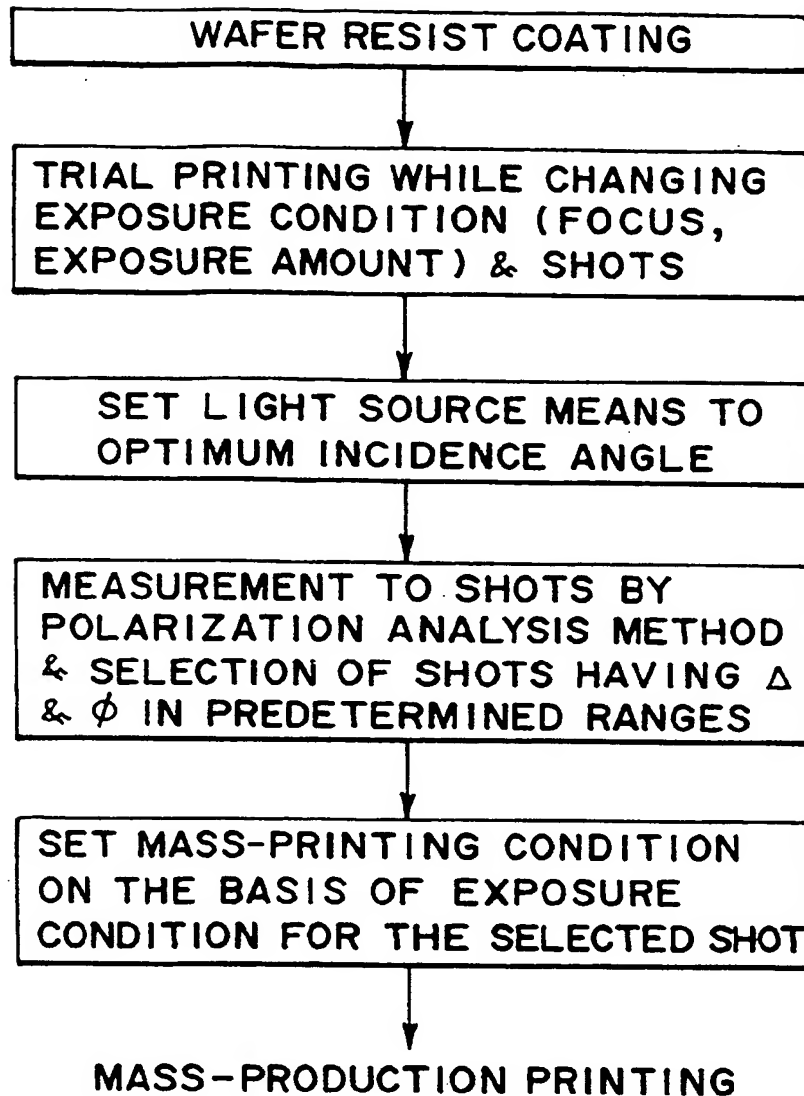


FIG. 9

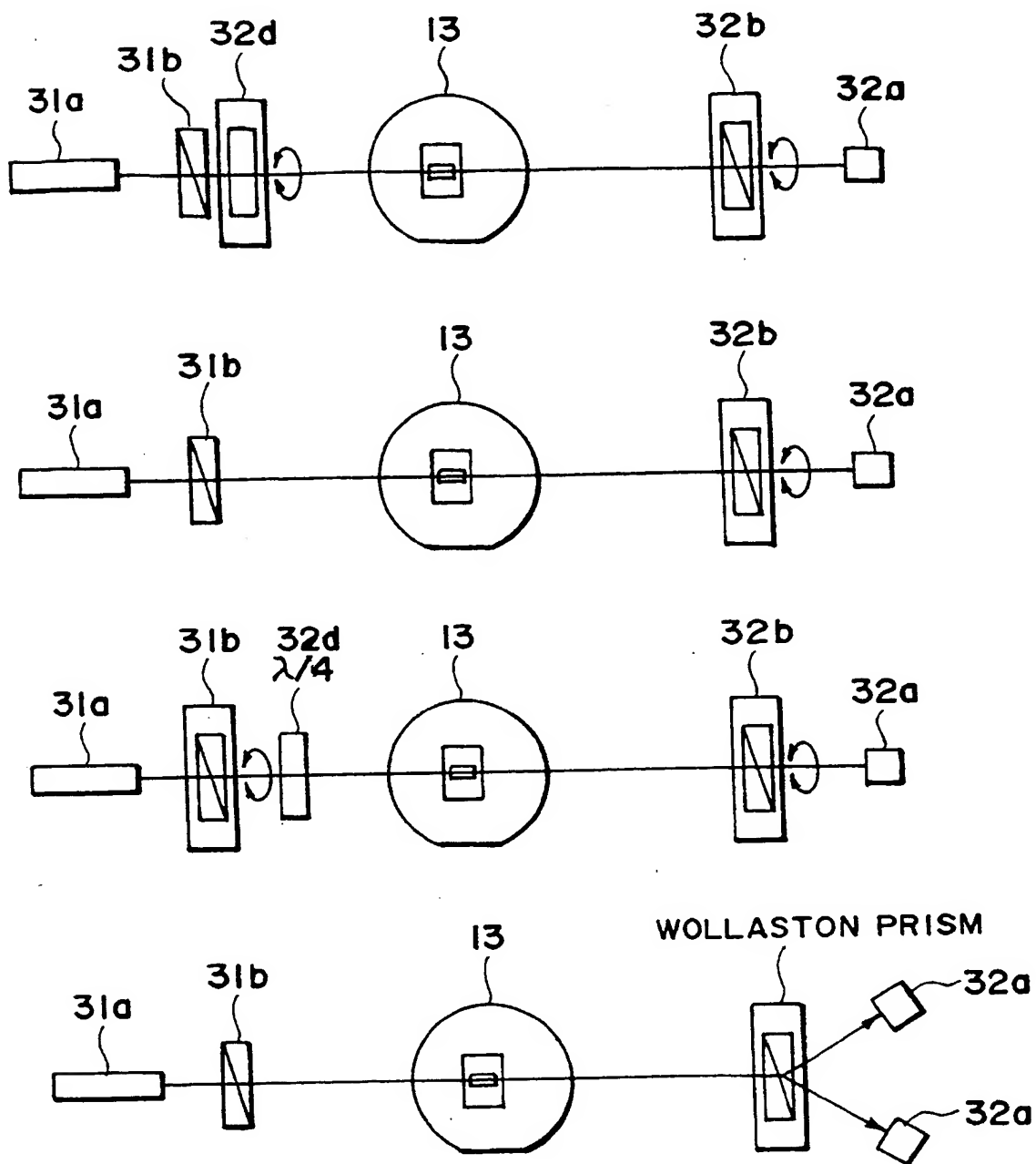


FIG. 10

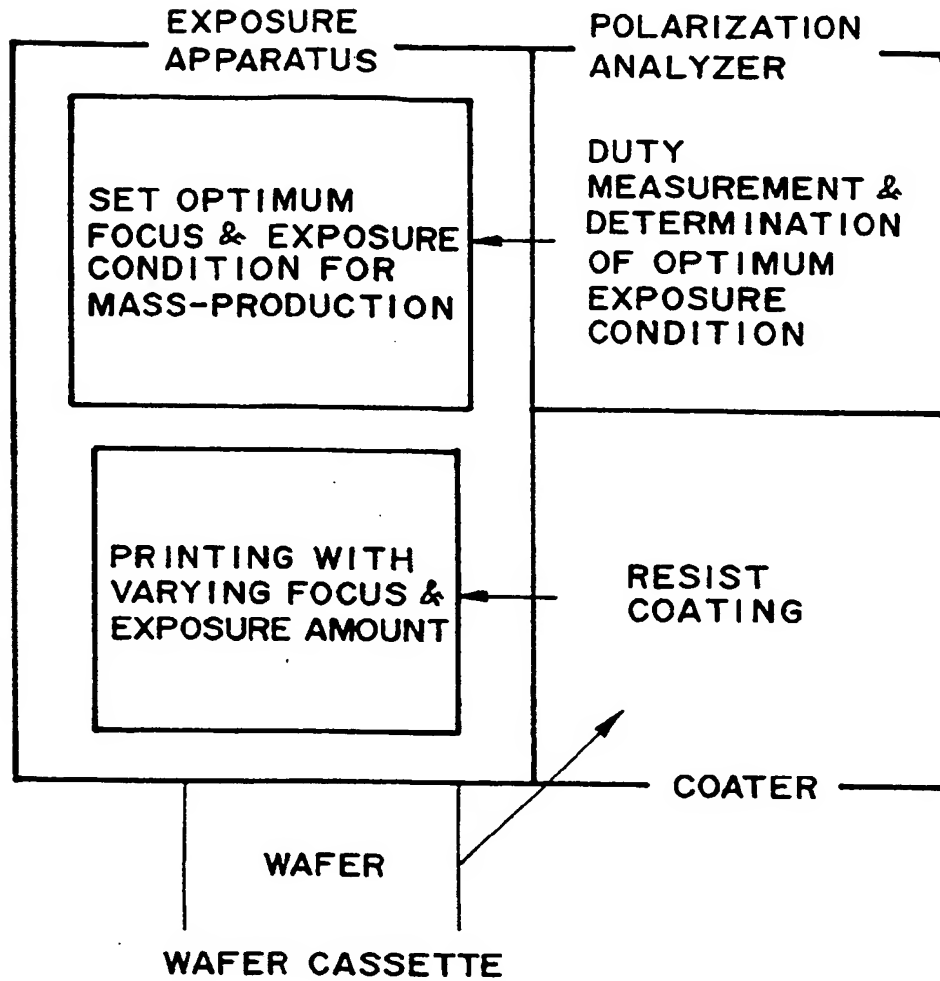


FIG. II

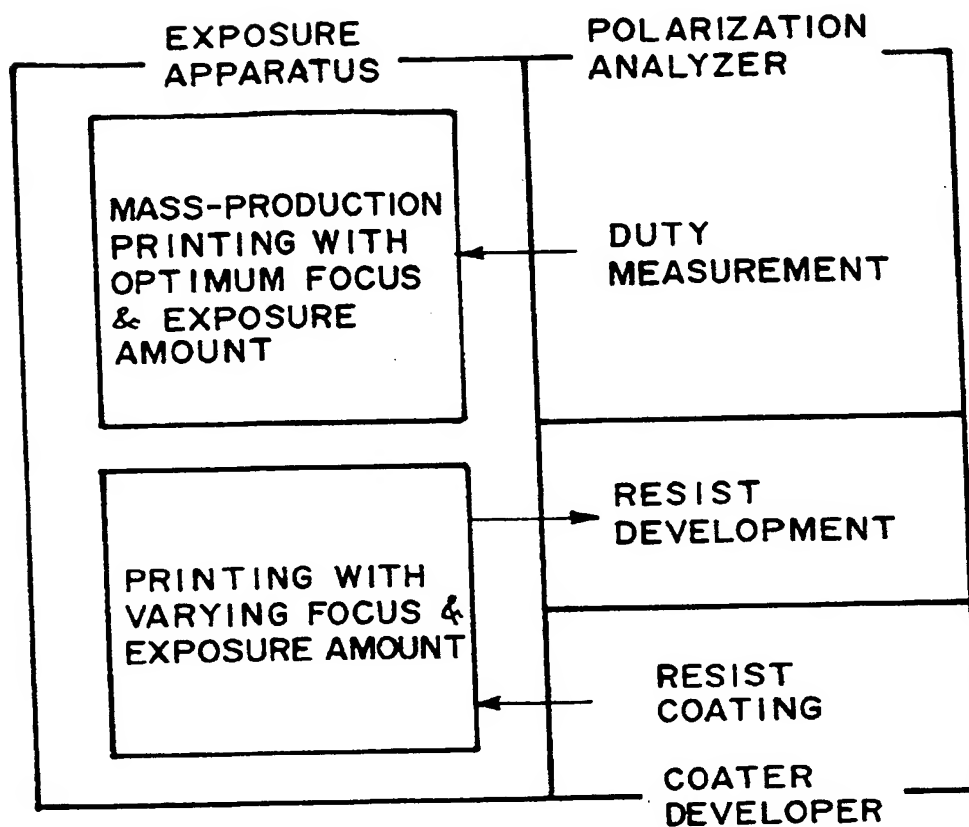


FIG. 12

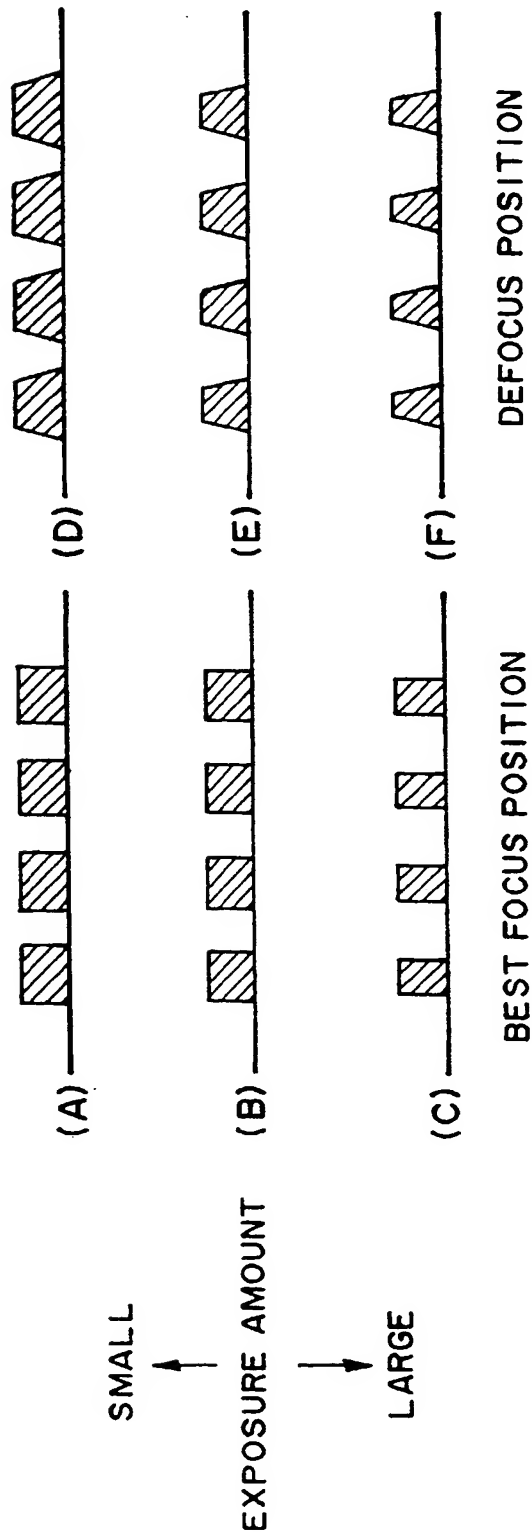


FIG. 13

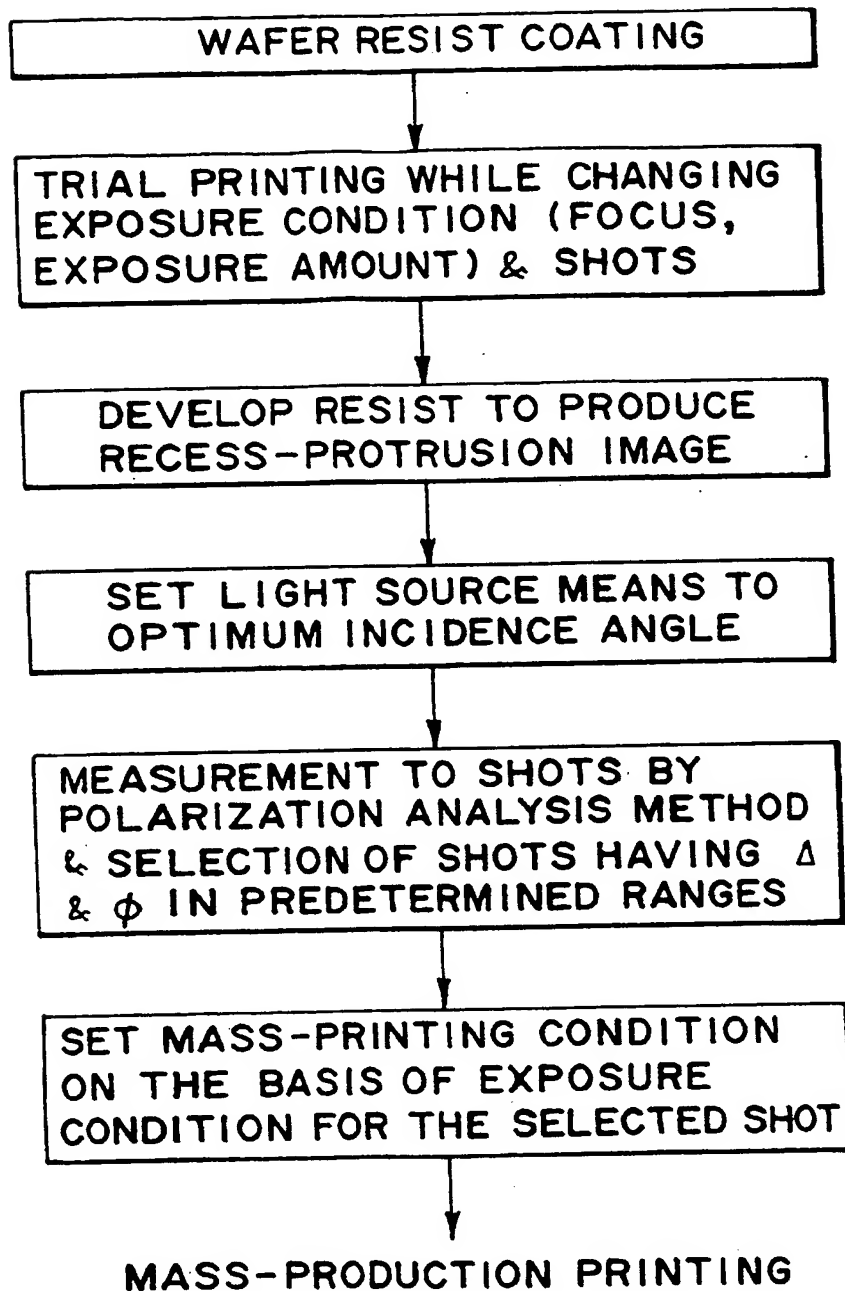


FIG. 14

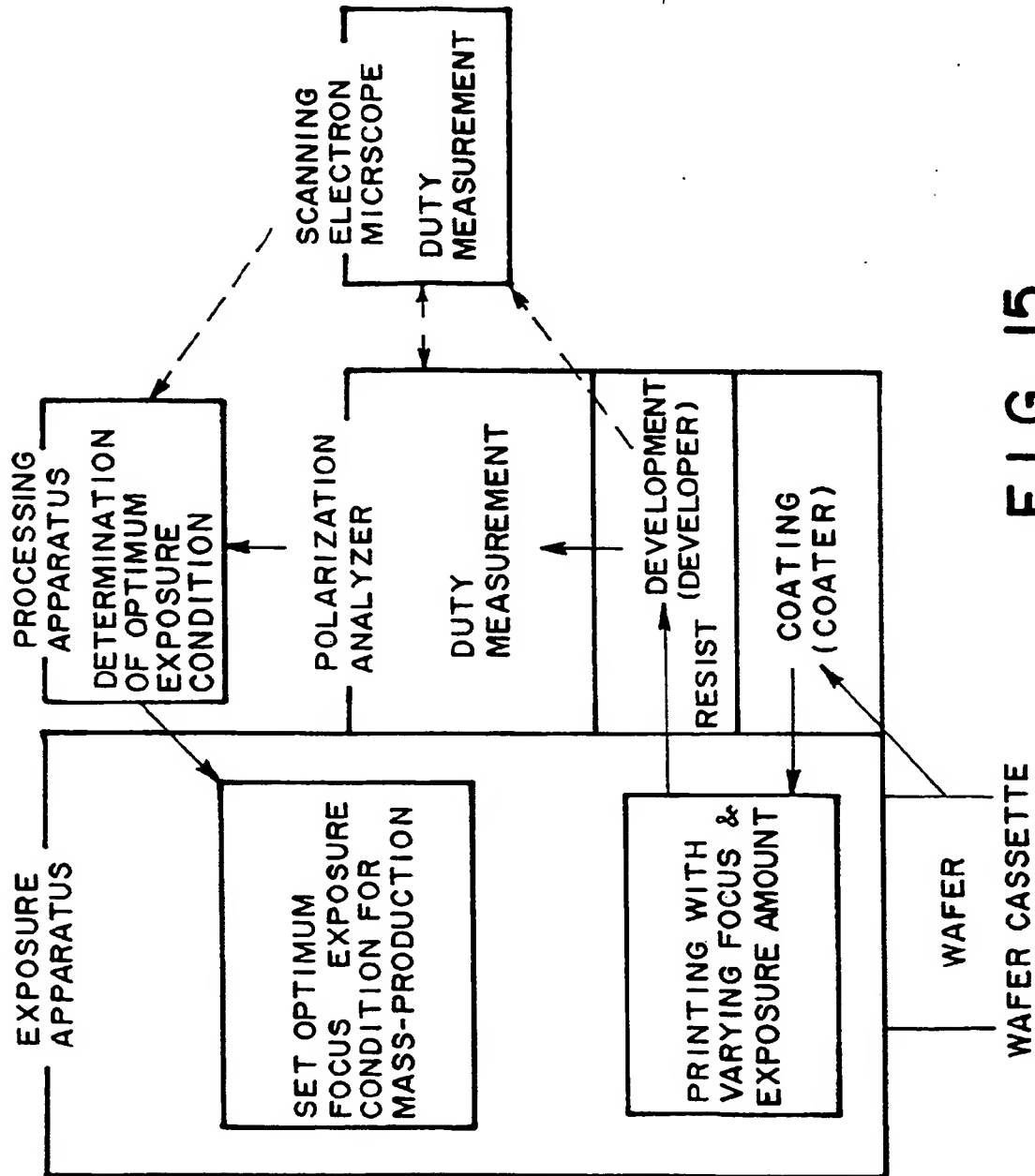


FIG. 15

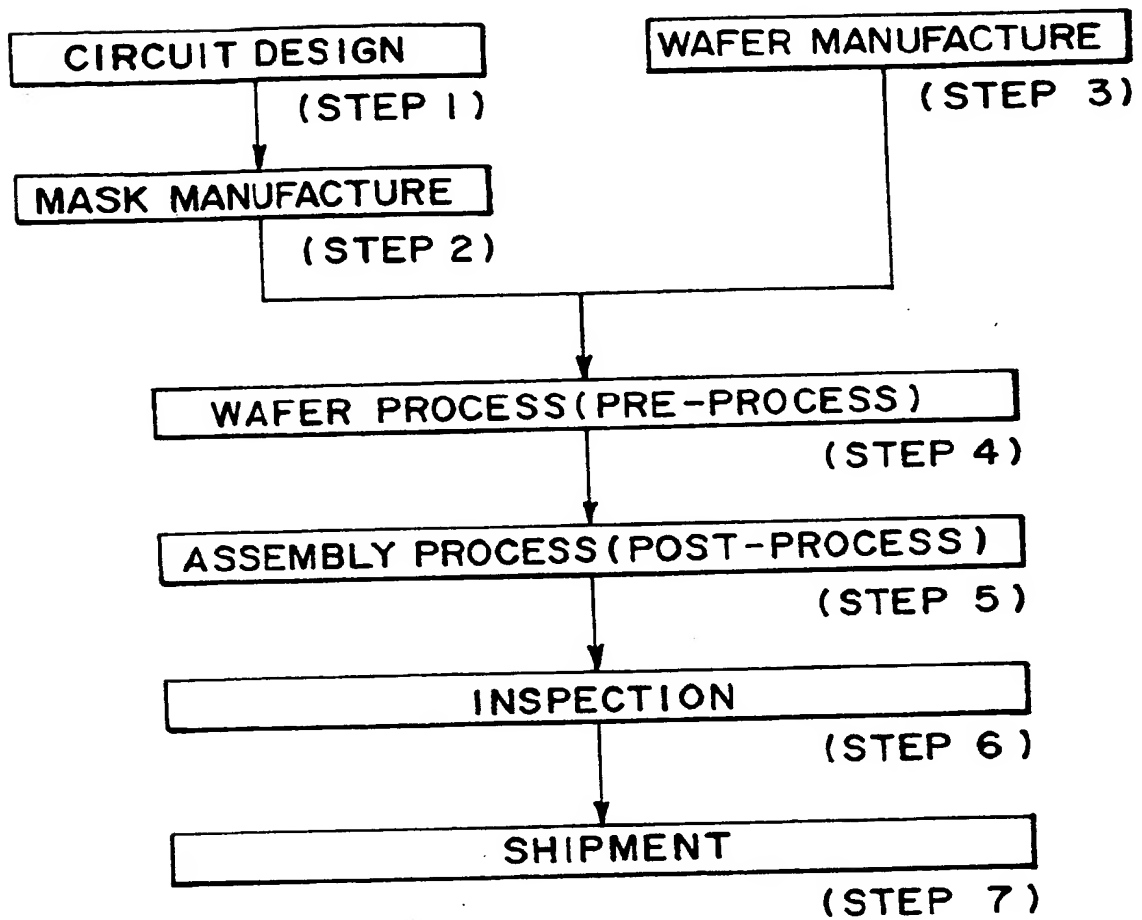


FIG. 16

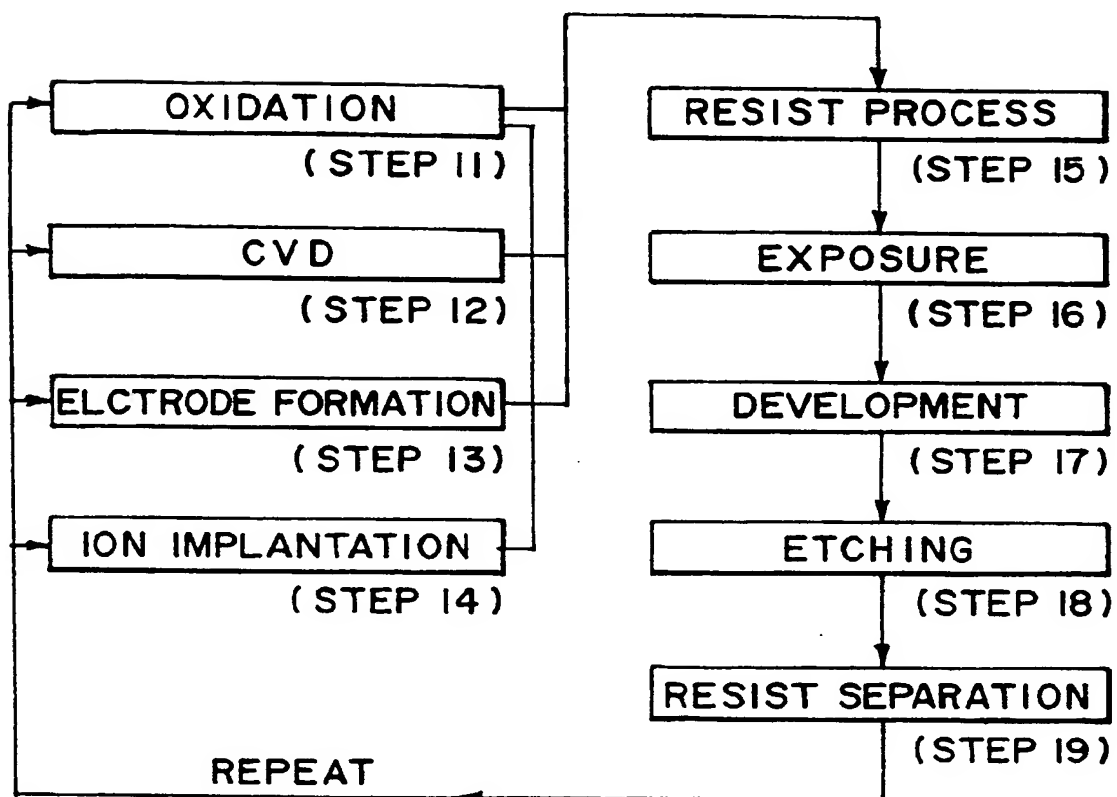


FIG. 17

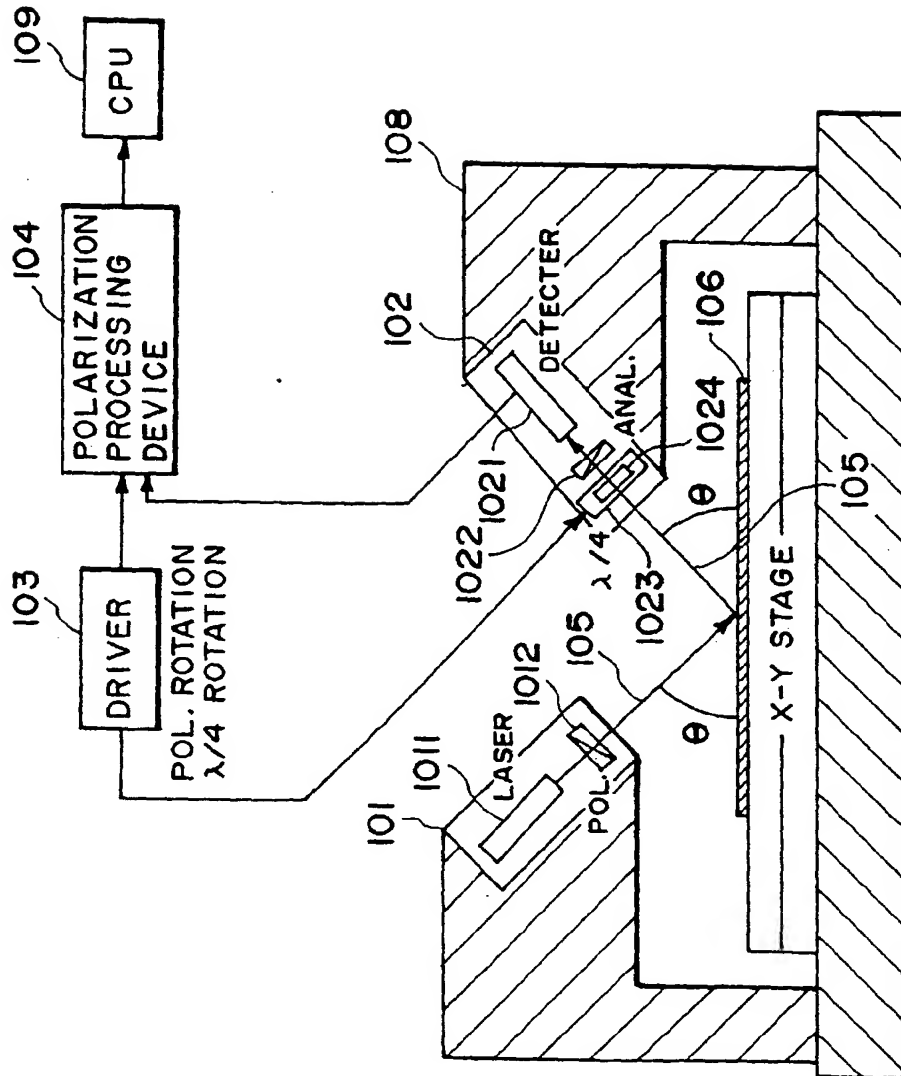


FIG. 18

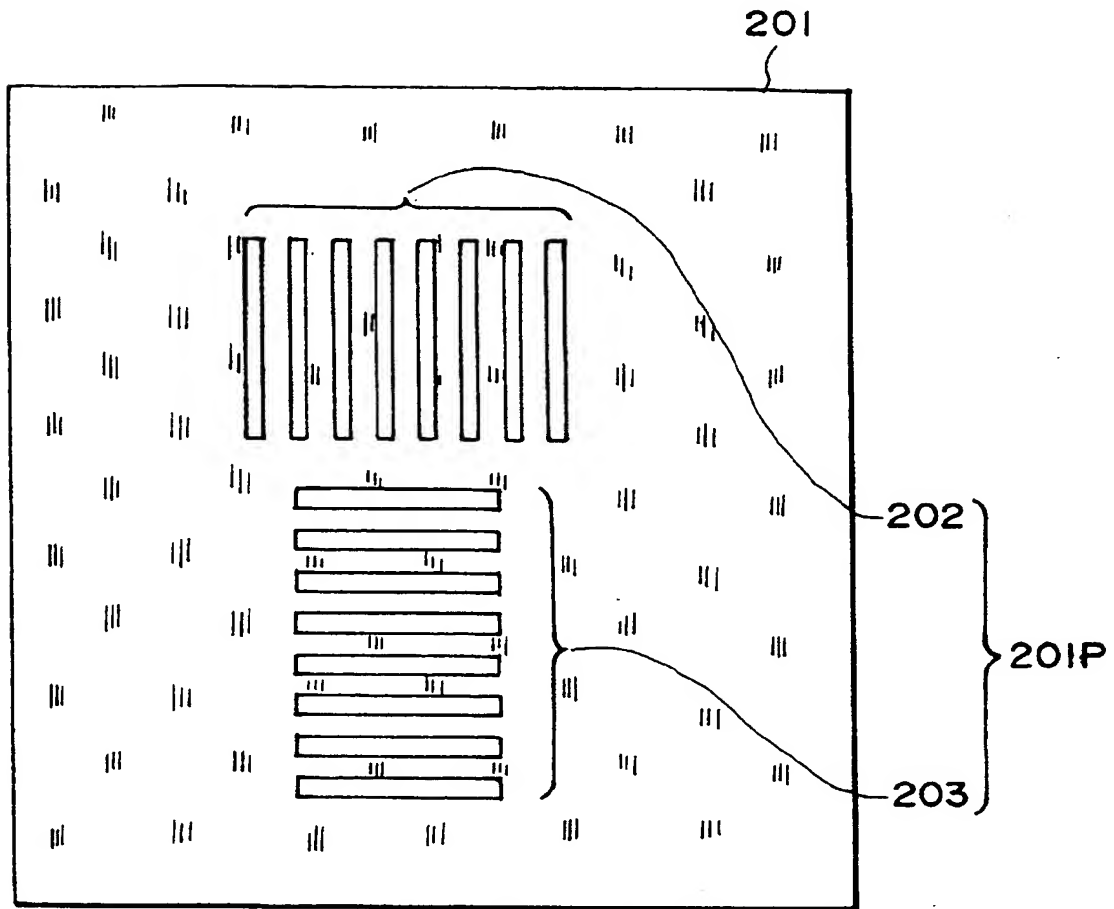


FIG. 19

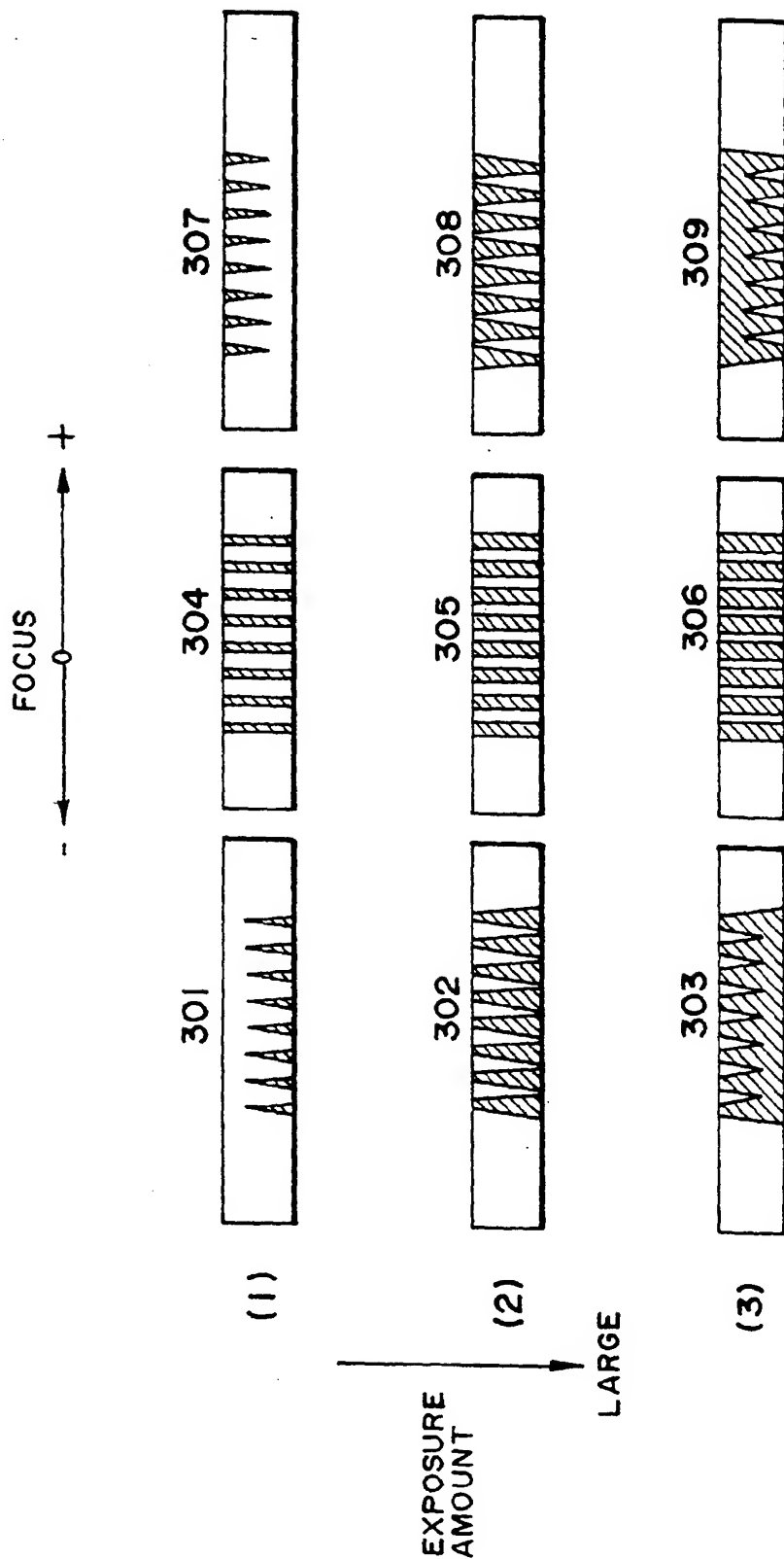


FIG. 20

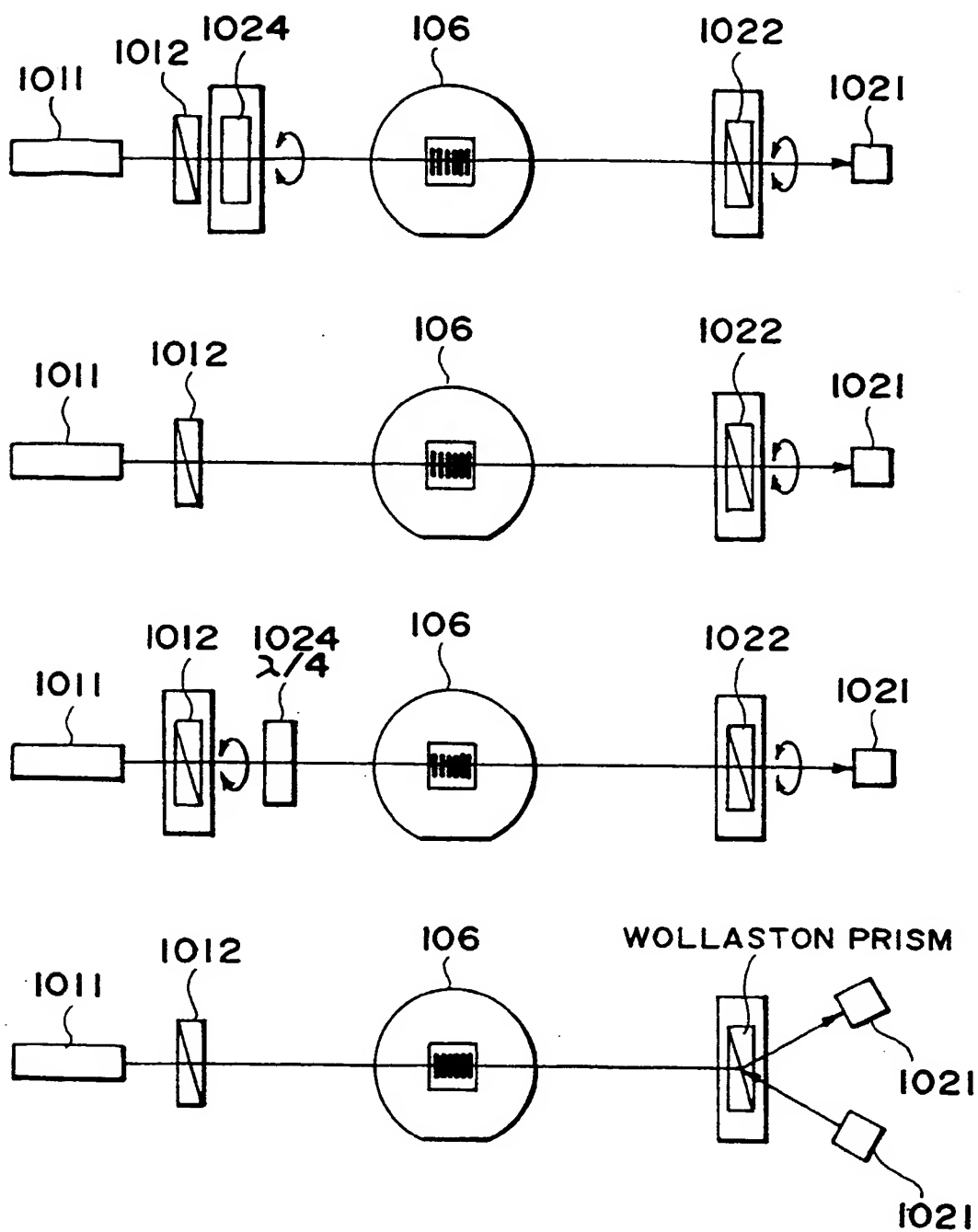


FIG. 21

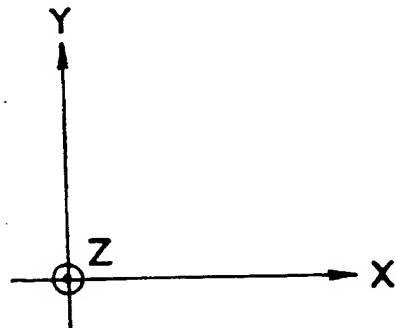
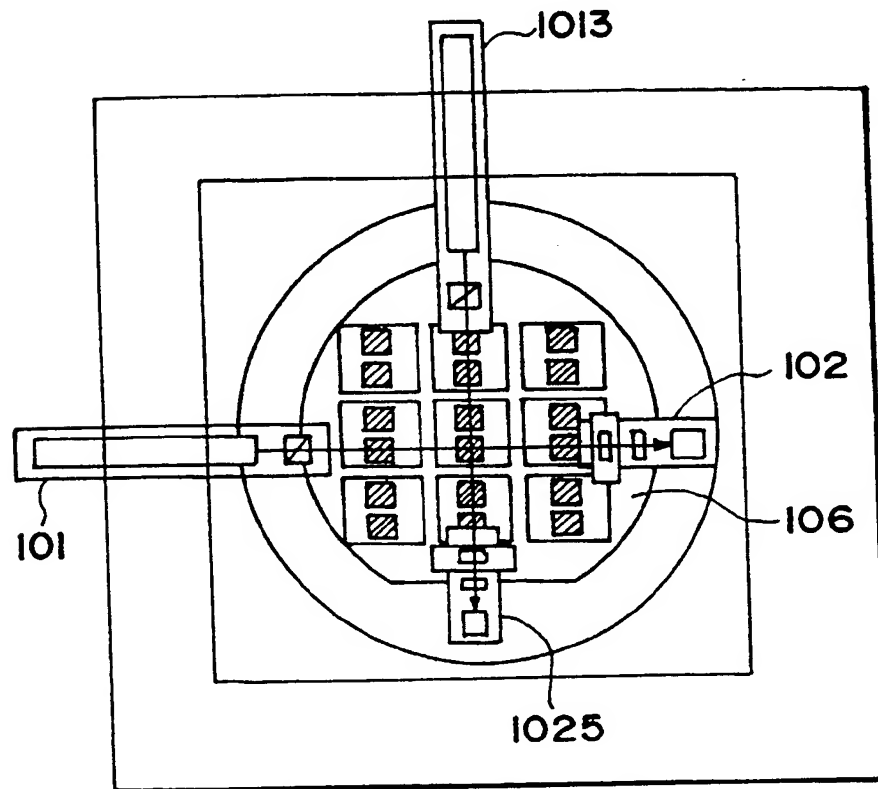


FIG. 22

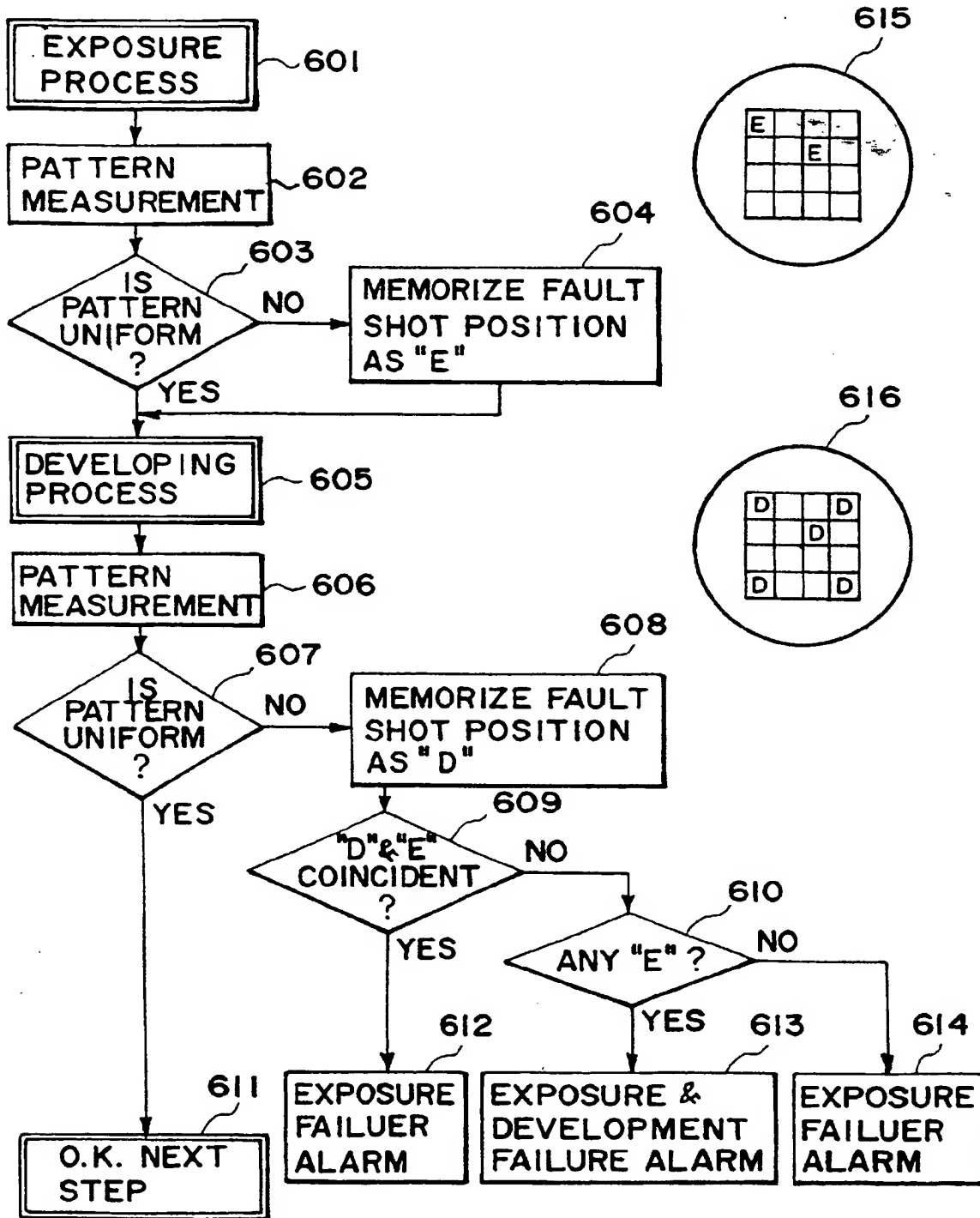


FIG. 23

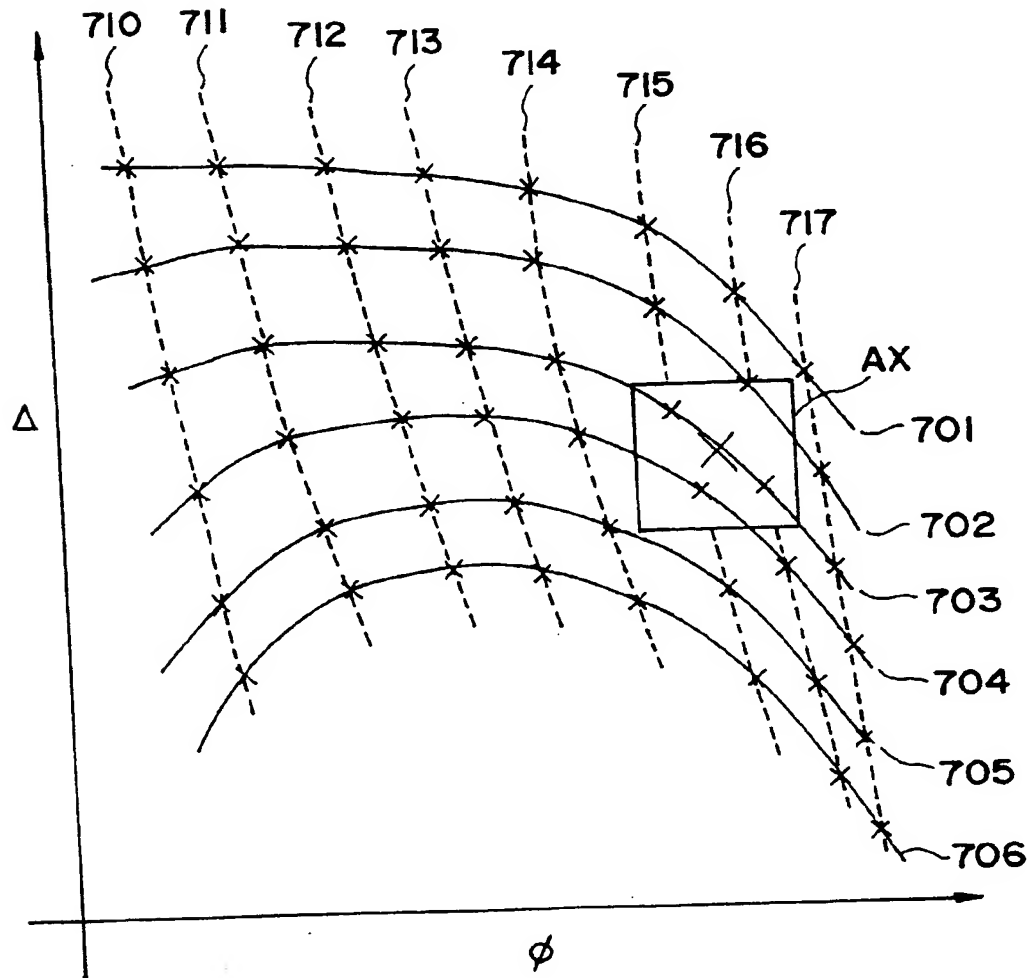


FIG. 24

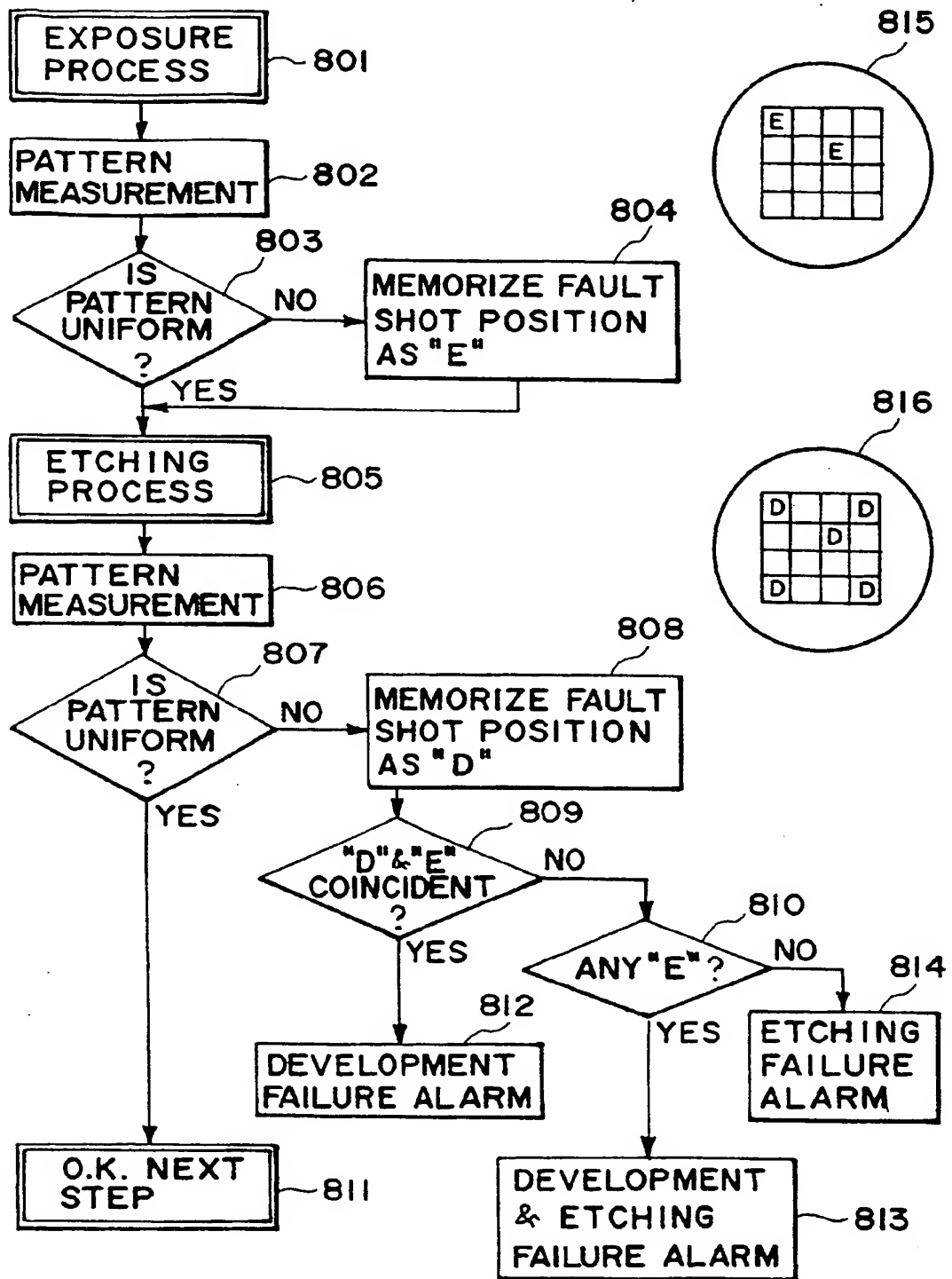


FIG. 25

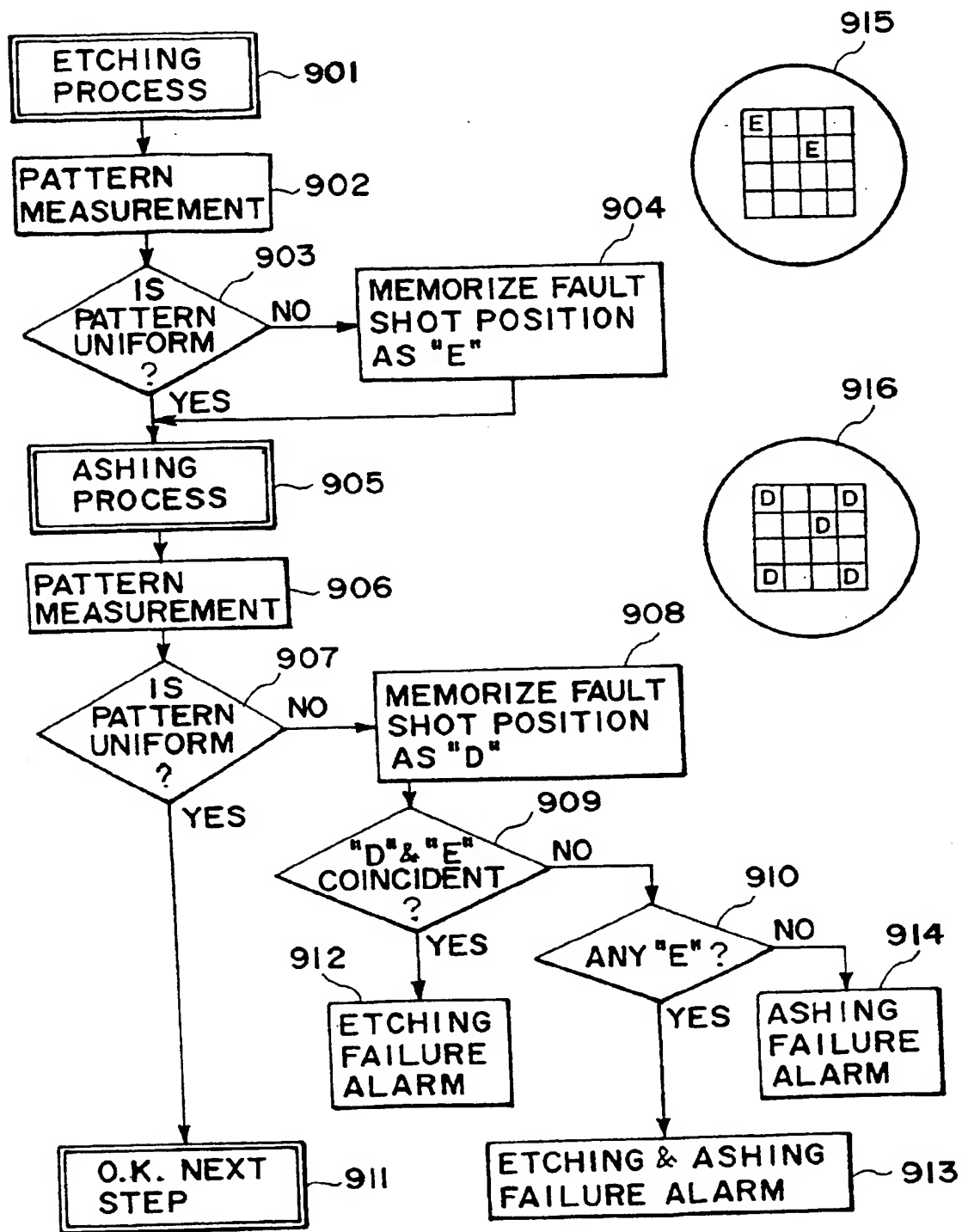


FIG. 26

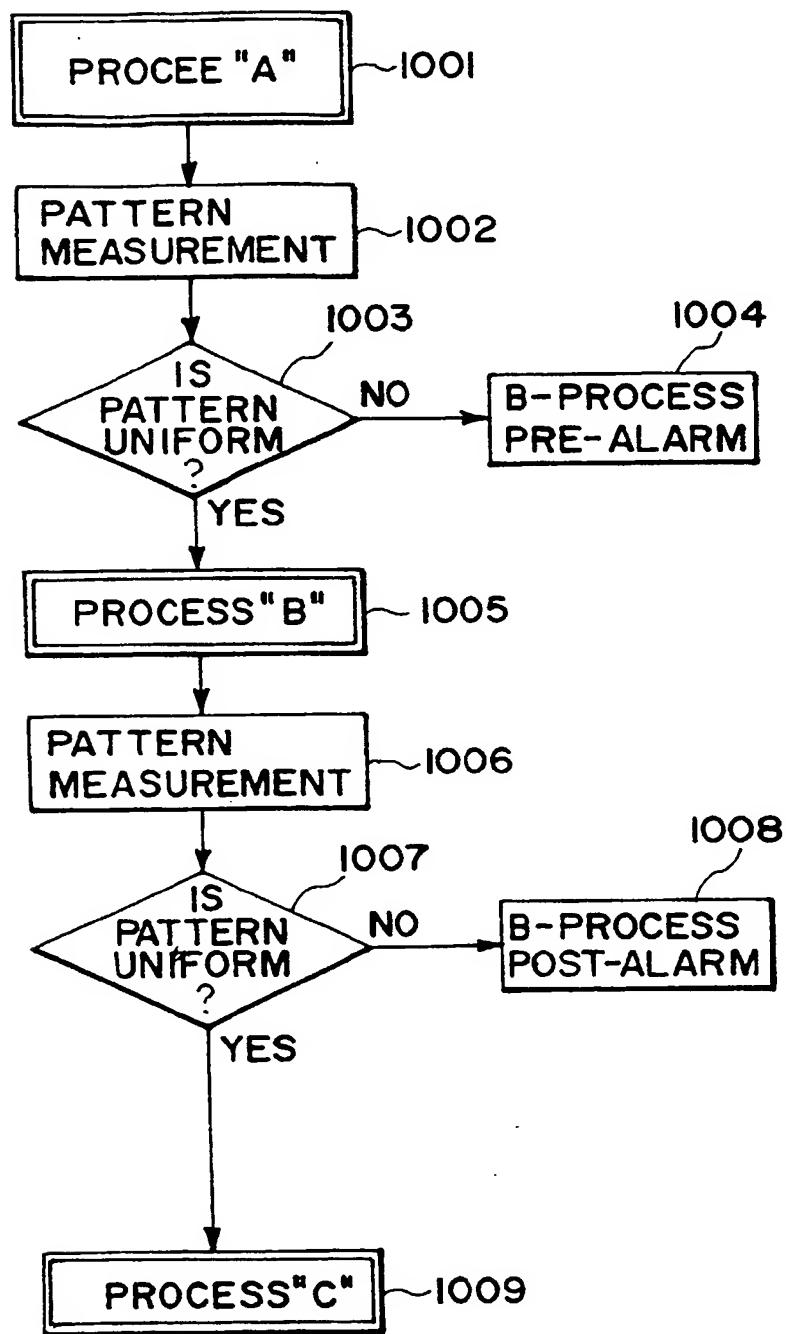


FIG. 27





(12)

**EUROPEAN PATENT APPLICATION**

(88) Date of publication A3:  
26.05.1999 Bull tin 1999/21

(51) Int Cl.<sup>6</sup>: **G03F 7/20**

(43) Date of publication A2:  
07.01.1998 Bulletin 1998/02

(21) Application number: 97304889.5

(22) Date of filing: 04.07.1997

(84) Designated Contracting States:  
AT BE CH DE DK ES FI FR GB GR IE IT LI LU MC  
NL PT SE

- **Yoshii, Minoru**  
**Ohta-ku, Tokyo (JP)**

(30) Priority: 05.07.1996 JP 176432/96  
04.10.1996 JP 264383/96

(74) Representative:  
**Beresford, Keith Denis Lewis et al**  
**BERESFORD & Co.**  
**2-5 Warwick Court**  
**High Holborn**  
**London WC1R 5DJ (GB)**

(71) Applicant: **CANON KABUSHIKI KAISHA**  
**Tokyo (JP)**

(72) Inventors:  
• Takeuchi, Seiji  
Ohta-ku, Tokyo (JP)

(54) **Exposure apparatus**

(57) A pattern inspection system for detecting a state of a pattern formed on an object (13), includes a light projecting device (31a) for projecting input light on to a sensitized pattern defined on the object, a light receiving device (32a) for receiving signal light from the sensitized pattern, a processing device (34) for detecting a change in the light by use of a signal from the light receiving device to detect the state of formation of the sensitized pattern, and a control device (33,54) for changing a condition of incidence (angle, wavelength, polarisation, intensity) of light from the light projecting device.

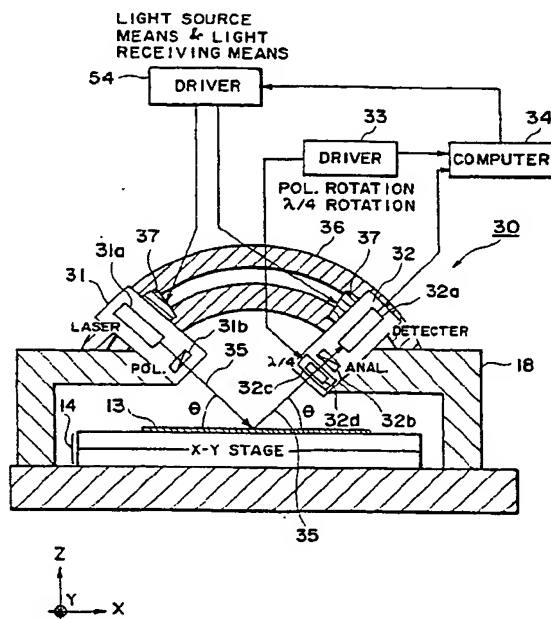


FIG. 2



European Patent  
Office

# EUROPEAN SEARCH REPORT

Application Number  
EP 97 30 4889

DOCUMENTS CONSIDERED TO BE RELEVANT			
Category	Citation of document with indication, where appropriate, of relevant passages	Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int.Cl.6)
X	US 5 516 608 A (HOBBS PHILIP C D ET AL) 14 May 1996  * column 1, line 1 - line 63 * * column 2, line 57 - line 67 * * column 3, line 19 - line 60 * * column 4, line 18 - line 27 * * figures 1,5,6A,6B *	1,4-6,9, 11,13, 16-18, 21,23, 25, 28-31, 35,37,55	G03F7/20
Y	---	2,3,12, 14,15, 24,26, 27,32,38	
Y	EP 0 502 679 A (AMERICAN TELEPHONE & TELEGRAPH) 9 September 1992  * column 2, line 14 - column 3, line 37 * * column 6, line 50 - column 7, line 48 * * figures *	2,3,12, 14,15, 24,26, 27,32,38	TECHNICAL FIELDS SEARCHED (Int.Cl.6)  G03F
X	EP 0 444 450 A (IBM) 4 September 1991  * page 4, line 5 - line 13 * * page 6, line 3 - page 7, line 1 * * figure 2 *  --- -/--	1-3,9, 11, 13-15, 21,23, 25-27, 35,37,55	
The present search report has been drawn up for all claims			
Place of search <b>THE HAGUE</b>		Date of completion of the search <b>25 March 1999</b>	Examiner <b>Heryet, C</b>
CATEGORY OF CITED DOCUMENTS X: particularly relevant if taken alone Y: particularly relevant if combined with another document of the same category A: technological background O: non-written disclosure P: intermediate document		T: theory or principle underlying the invention E: earlier patent document, but published on, or after the filing date D: document cited in the application L: document cited for other reasons --- &: member of the same patent family, corresponding document	

EPO FORM 1503 (03.82) (PUC01)



European Patent  
Office

Application Number

EP 97 30 4889

#### CLAIMS INCURRING FEES

The present European patent application comprised at the time of filing more than ten claims.

- ☐ Only part of the claims have been paid within the prescribed time limit. The present European search report has been drawn up for the first ten claims and for those claims for which claims fees have been paid, namely claim(s):
- ☐ No claims fees have been paid within the prescribed time limit. The present European search report has been drawn up for the first ten claims.

#### LACK OF UNITY OF INVENTION

The Search Division considers that the present European patent application does not comply with the requirements of unity of invention and relates to several inventions or groups of inventions, namely:

see sheet B

- ☒ All further search fees have been paid within the fixed time limit. The present European search report has been drawn up for all claims.
- ☐ Only part of the further search fees have been paid within the fixed time limit. The present European search report has been drawn up for those parts of the European patent application which relate to the inventions in respect of which search fees have been paid, namely claims:
- ☐ None of the further search fees have been paid within the fixed time limit. The present European search report has been drawn up for those parts of the European patent application which relate to the invention first mentioned in the claims, namely claims:



European Patent  
Office

# EUROPEAN SEARCH REPORT

Application Number  
EP 97 30 4889

DOCUMENTS CONSIDERED TO BE RELEVANT			
Category	Citation of document with indication, where appropriate, of relevant passages	Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int.Cl.6)
P,X	PATENT ABSTRACTS OF JAPAN vol. 097, no. 006, 30 June 1997 & JP 09 036037 A (CANON INC), 7 February 1997  & US 5 777 744 A (YOSHII ET AL.) 7 July 1998 * the whole document *	1-3,7,9, 11, 13-15, 19,21, 23, 25-27, 33,35, 37,55	TECHNICAL FIELDS SEARCHED (Int.Cl.6)
X	US 5 252 414 A (YAMASHITA KAZUHIRO ET AL) 12 October 1993  * column 5, line 3 - column 6, line 21 * * figures *	39,41, 42,45, 47,49, 50,53	
X	US 5 468 580 A (TANAKA YASUSHI) 21 November 1995 * column 14, line 5 - line 47 * * column 15, line 33 - column 18, line 11 * * figures 10-13 *	39,46, 47,54	
The present search report has been drawn up for all claims			
Place of search <b>THE HAGUE</b>		Date of completion of the search <b>25 March 1999</b>	Examiner <b>Heryet, C</b>
<p><b>CATEGORY OF CITED DOCUMENTS</b></p> <p>X : particularly relevant if taken alone Y : particularly relevant if combined with another document of the same category A : technological background O : non-written disclosure P : intermediate document</p> <p>T : theory or principle underlying the invention E : earlier patent document, but published on, or after the filing date D : document cited in the application L : document cited for other reasons &amp; : member of the same patent family, corresponding document</p>			

EPO FORM 1503 03/92 (P04/C01)



European Patent  
Office

LACK OF UNITY OF INVENTION  
SHEET B

Application Number

EP 97 30 4889

The Search Division considers that the present European patent application does not comply with the requirements of unity of invention and relates to several inventions or groups of inventions, namely:

1. Claims: 1-38, 55

Inspection of "sensitized pattern"

2. Claims: 39-54

Inspection of pattern before and after processing.

**ANNEX TO THE EUROPEAN SEARCH REPORT  
ON EUROPEAN PATENT APPLICATION NO.**

EP 97 30 4889

This annex lists the patent family members relating to the patent documents cited in the above-mentioned European search report.  
The members are as contained in the European Patent Office EDP file on  
The European Patent Office is in no way liable for these particulars which are merely given for the purpose of information.

25-03-1999

Patent document cited in search report		Publication date	Patent family member(s)	Publication date
US 5516608	A	14-05-1996	JP 7263339 A	13-10-1995
EP 0502679	A	09-09-1992	JP 7095522 B	11-10-1995
			JP 7169667 A	04-07-1995
			US 5362585 A	08-11-1994
EP 0444450	A	04-09-1991	US 5124927 A	23-06-1992
			DE 69121261 D	19-09-1996
			DE 69121261 T	20-02-1997
			JP 2019545 C	19-02-1996
			JP 5315220 A	26-11-1993
			JP 7060789 B	28-06-1995
US 5252414	A	12-10-1993	JP 2112526 C	21-11-1996
			JP 4101412 A	02-04-1992
			JP 8028321 B	21-03-1996
US 5468580	A	21-11-1995	JP 6132189 A	13-05-1994

EPO FORM P0459

For more details about this annex : see Official Journal of the European Patent Office, No. 12/82